

GMR Read head

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ECE, CMRR

Introduction to recording
Basic GMR sensor
Next generation heads TMR, CPP-GMR
Challenges



Product scaling



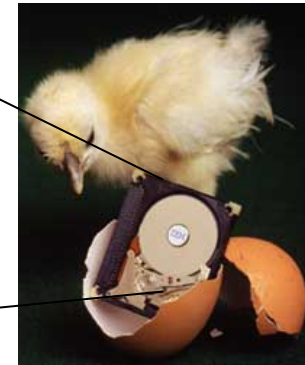
2 kbits/in²
70 kbits/s
50x 24 in dia disks
\$10,000/Mbyte

100 Gbyte
mobile drive



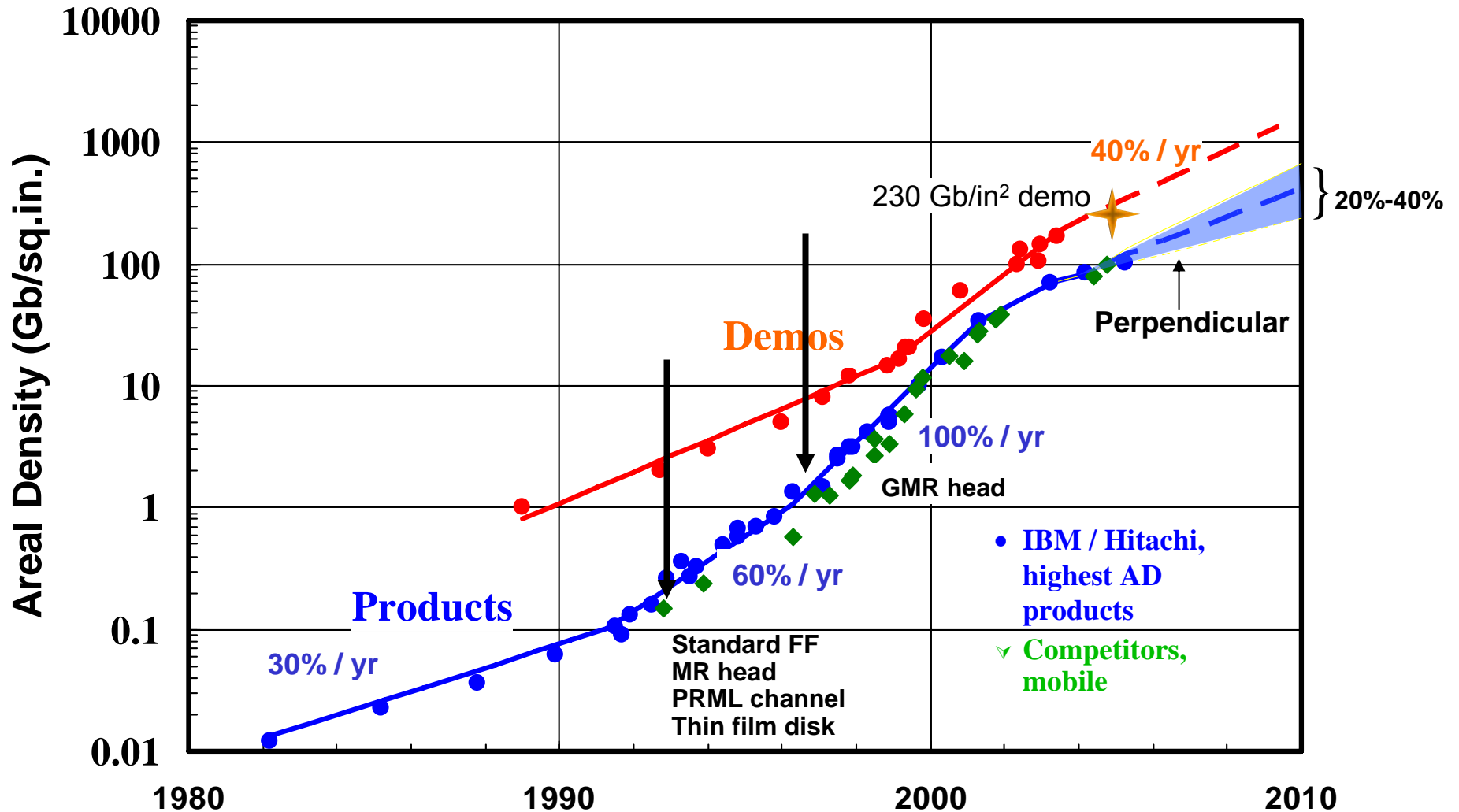
130 Gbits/in²
630 Mb/s
2 x 2.5" glass disks
<\$0.01/Mbyte

8 Gbyte



Microdrive
78 Gbits/in²
1 x 1" dia disk

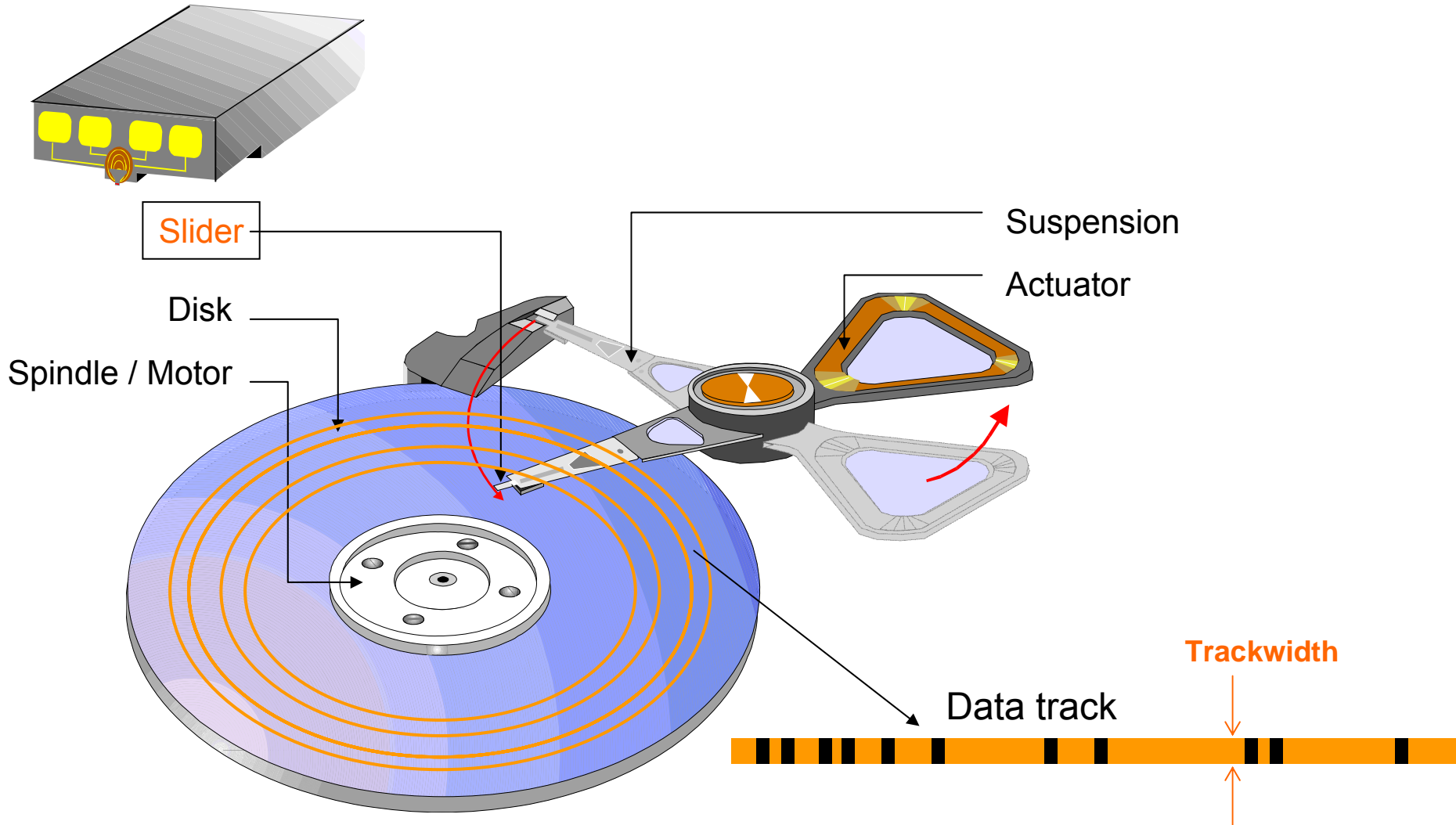
Areal density trends



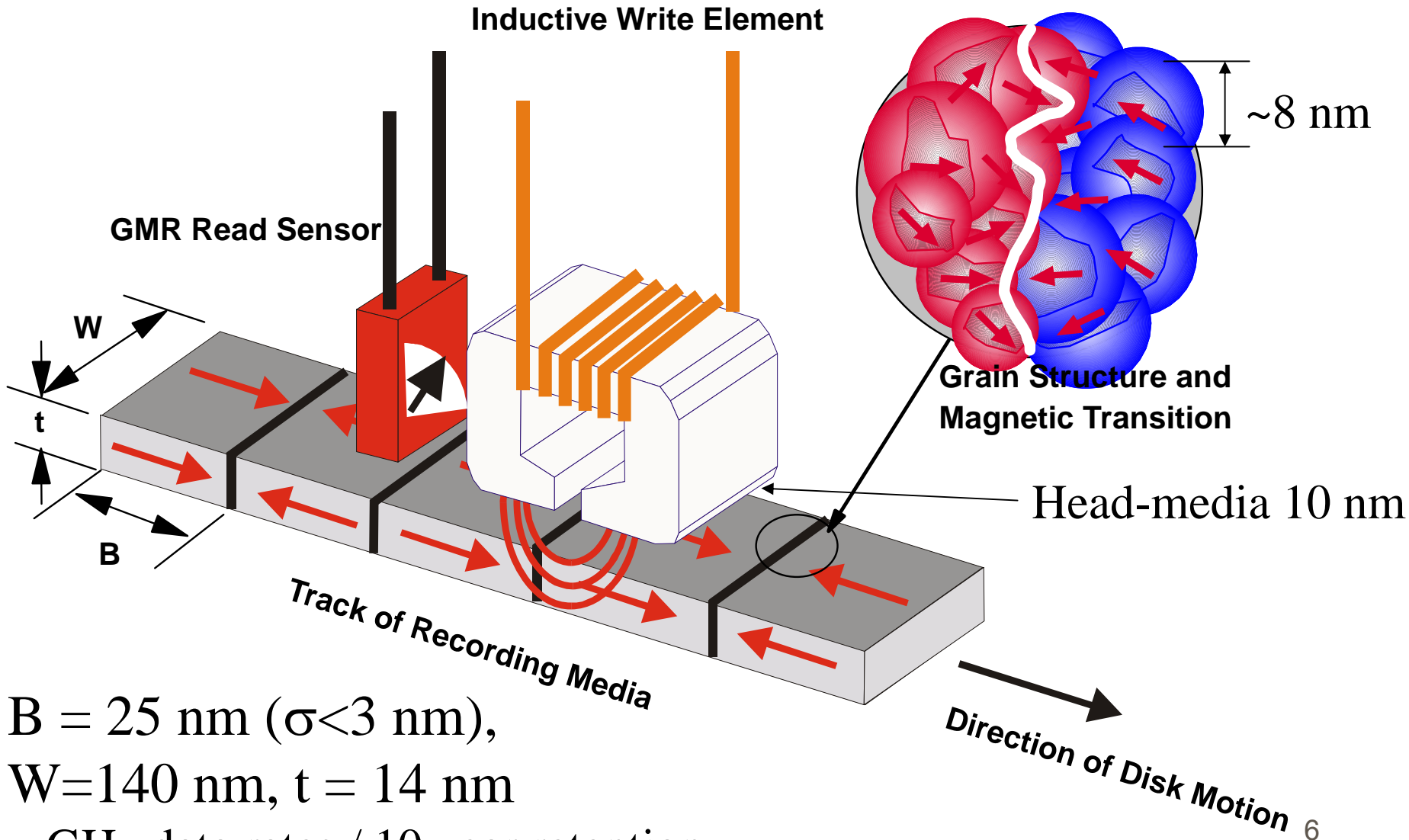
1975



Recording basics



Magnetic recording components

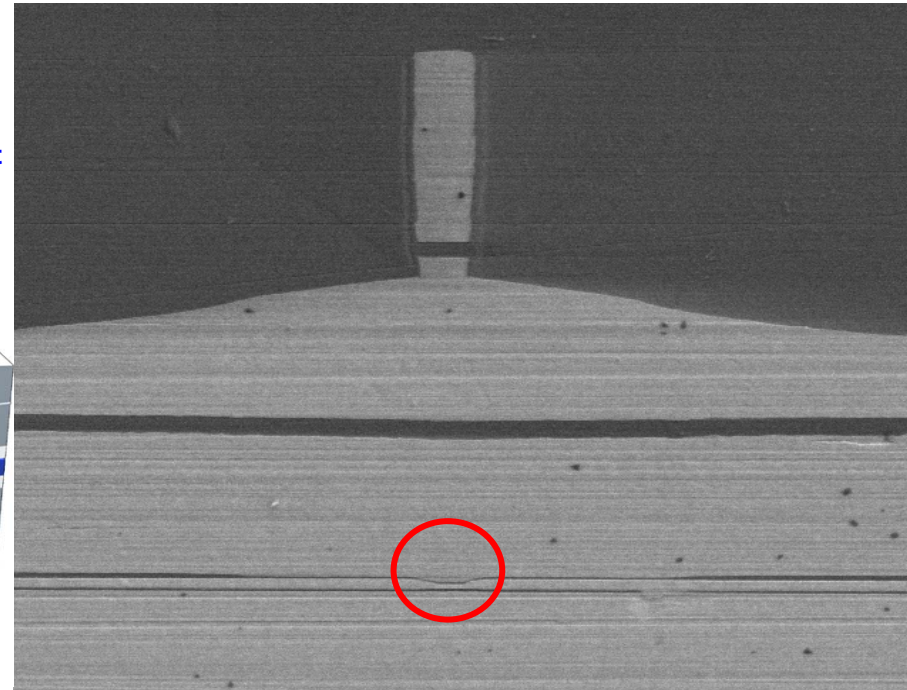
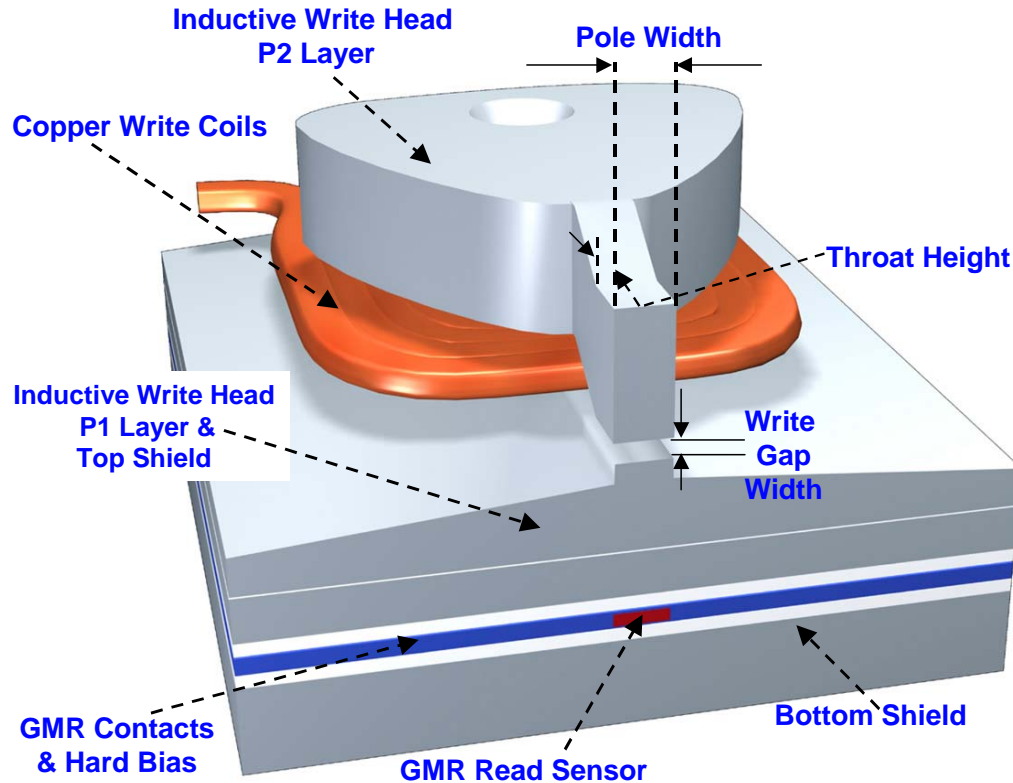


$B = 25$ nm ($\sigma < 3$ nm),

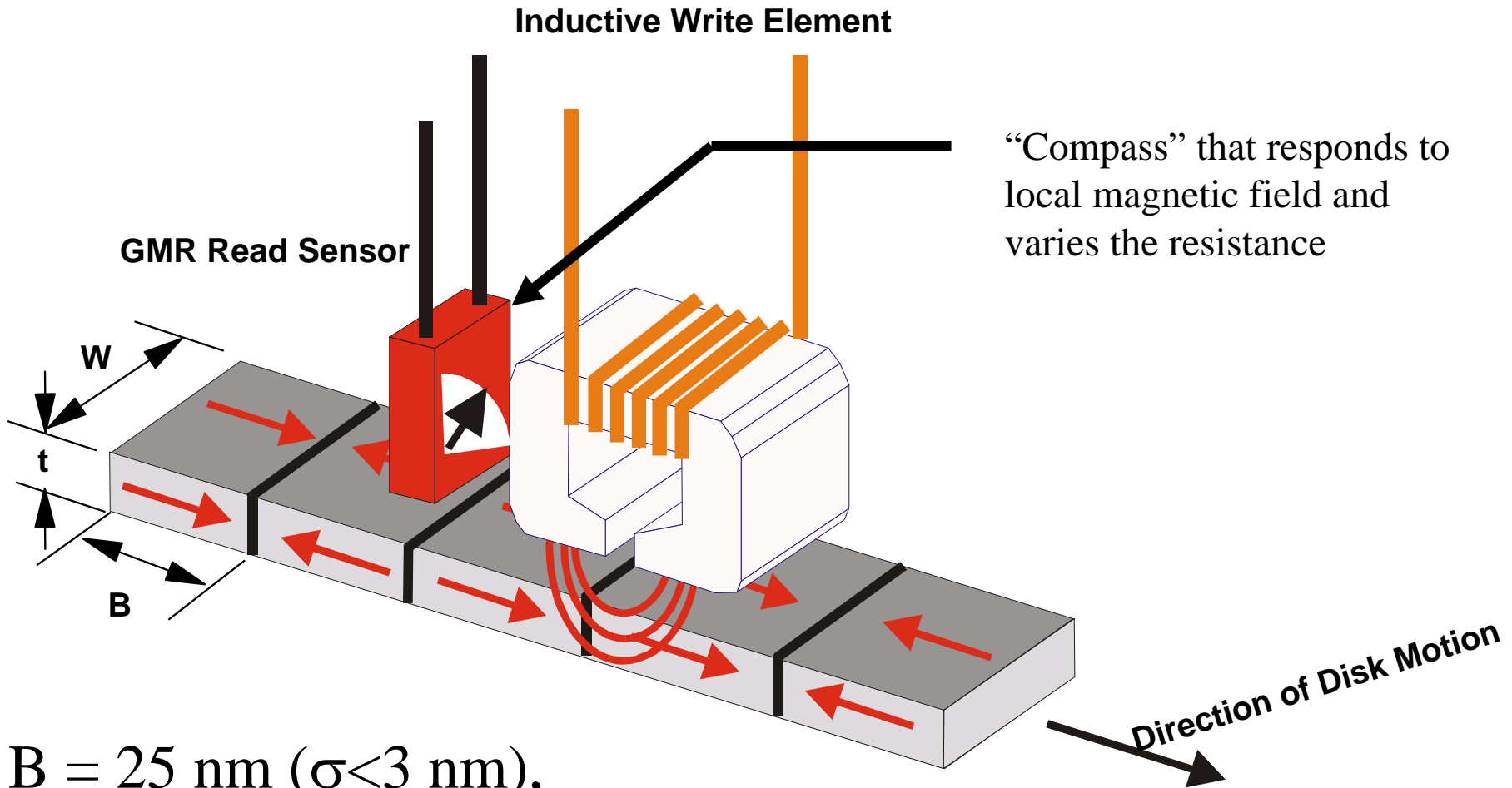
$W = 140$ nm, $t = 14$ nm

\sim GHz data rates / 10 year retention

Magnetic recording components

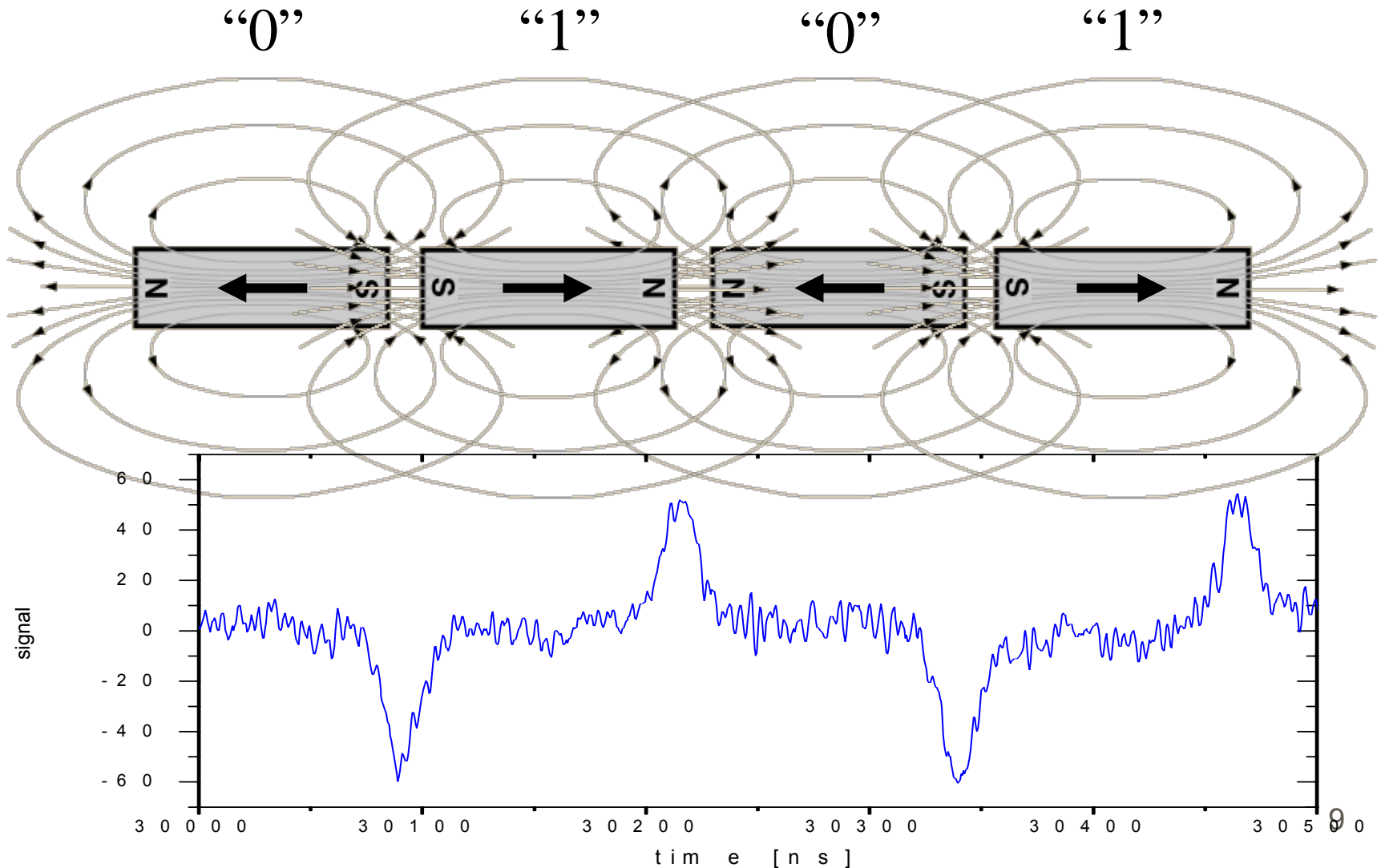


Magnetic recording components

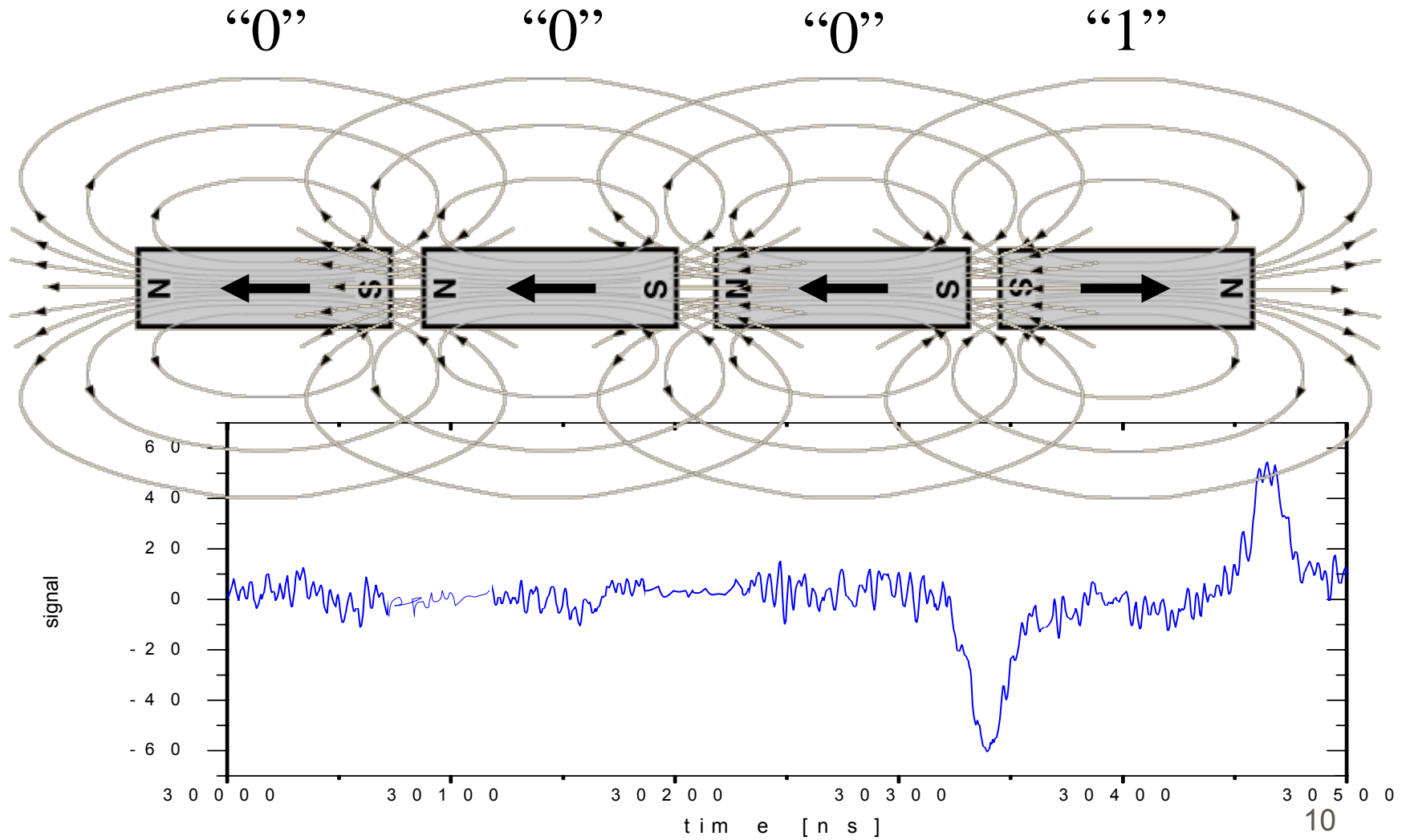


$B = 25 \text{ nm}$ ($\sigma < 3 \text{ nm}$),
 $W = 150 \text{ nm}$, $t = 14 \text{ nm}$
data rate $\sim \text{GHz}$

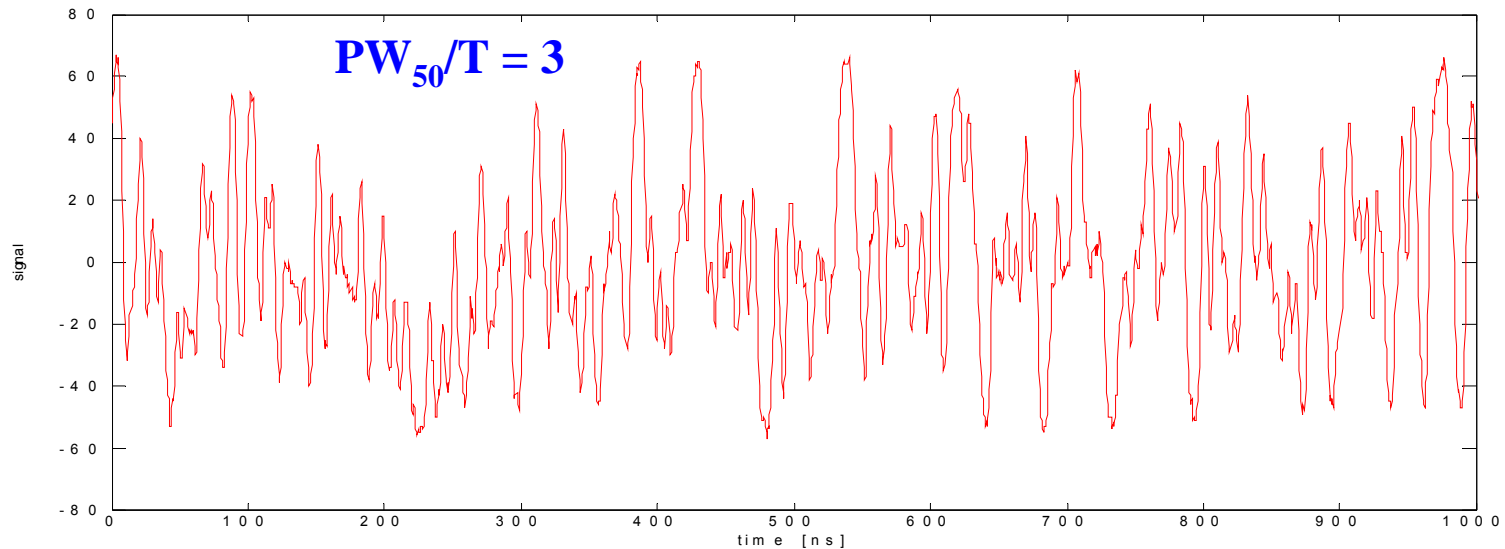
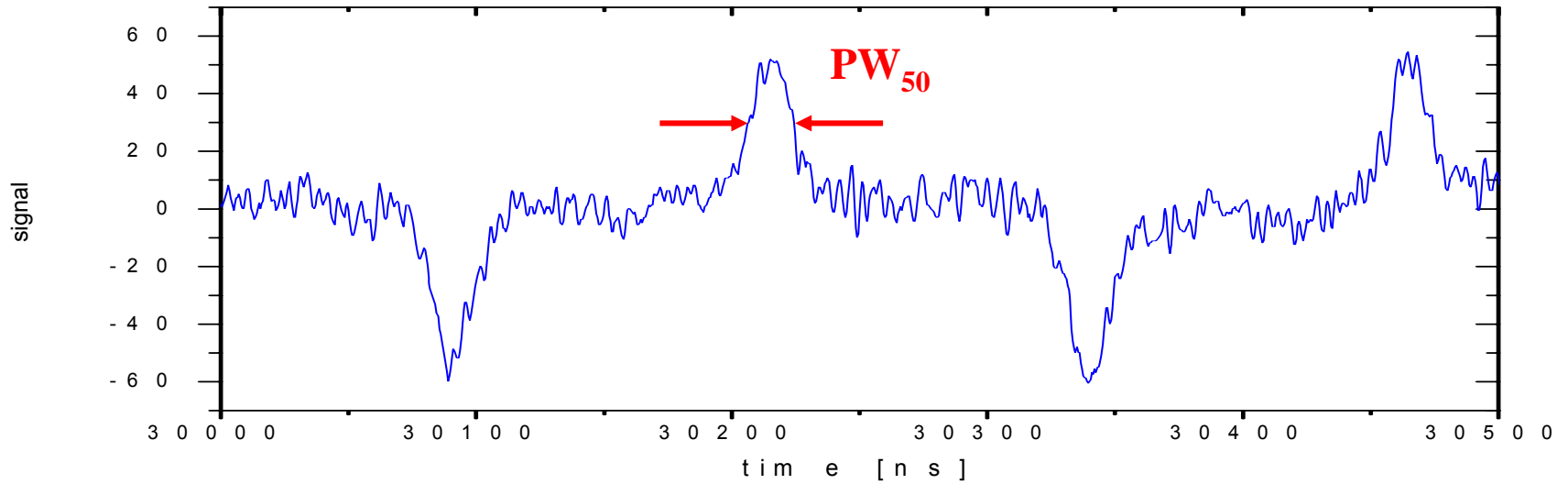
Recording basics



Recording basics



Magnetic resolution



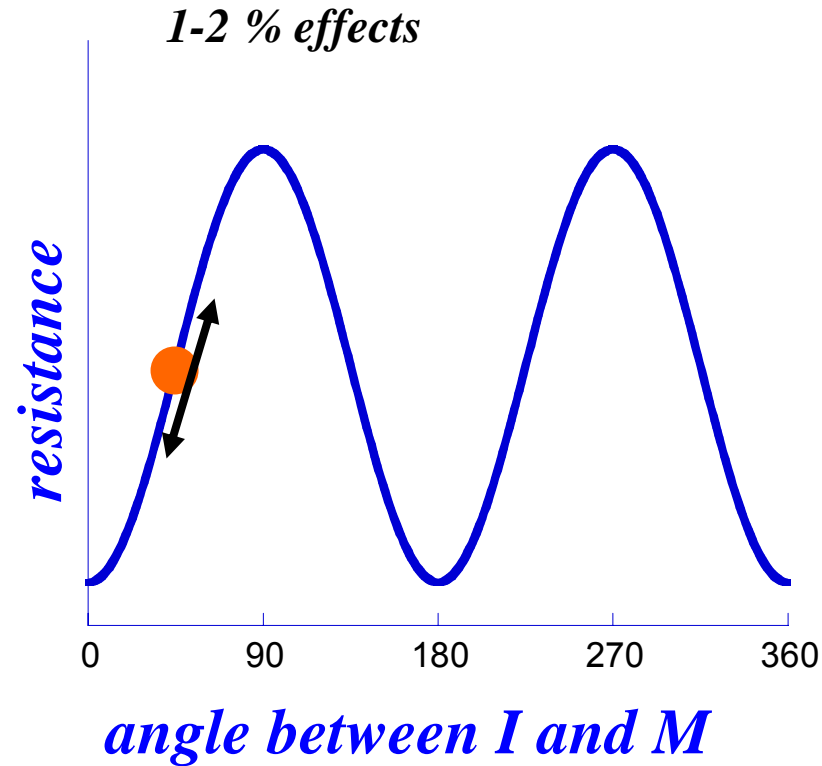
Anisotropic Magneto-resistance (AMR)



high resistance

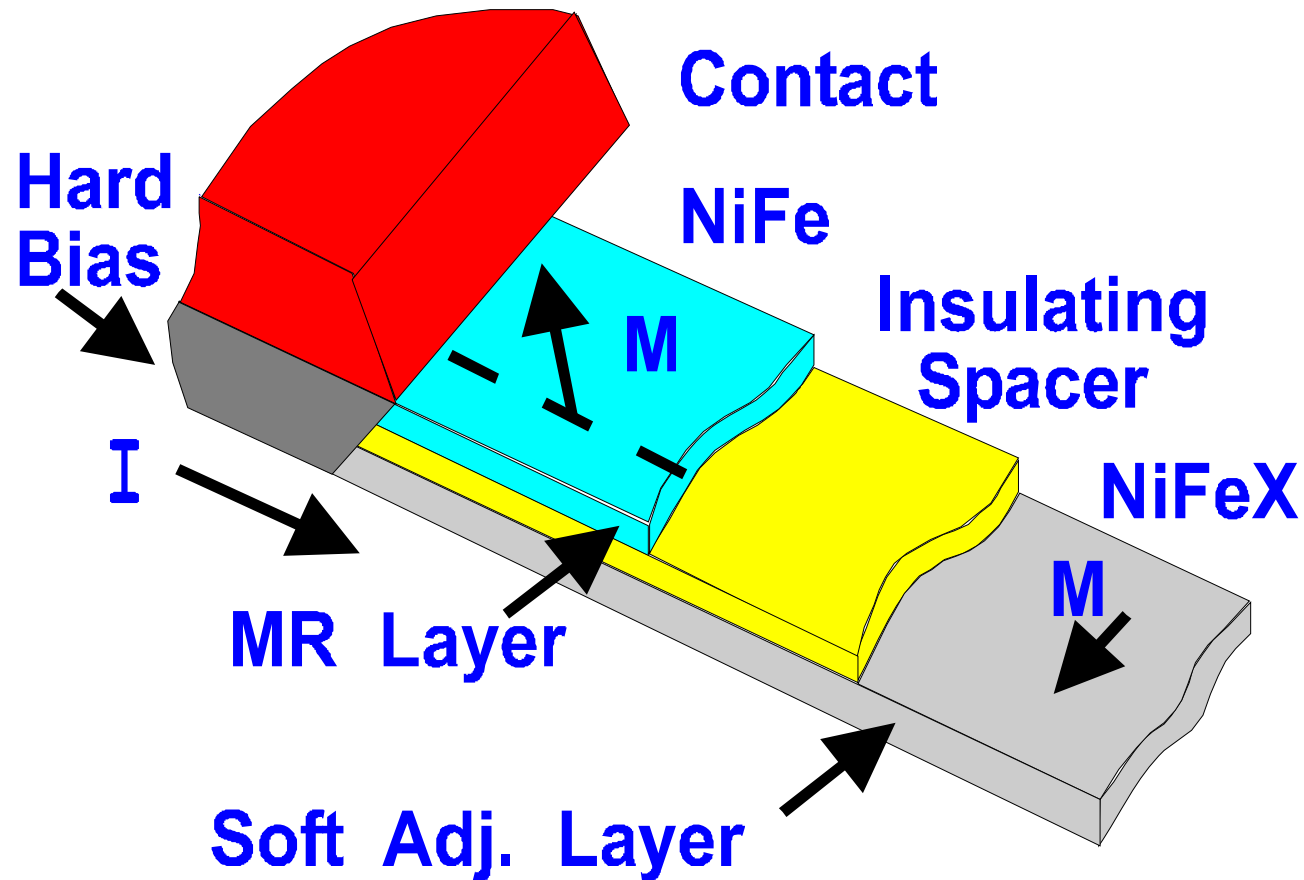


low resistance

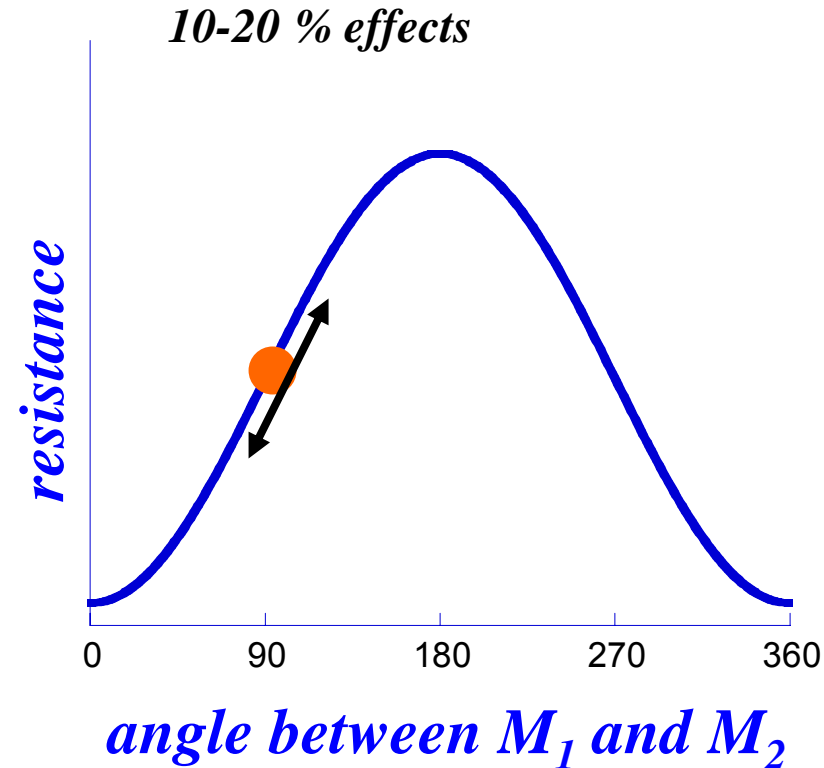
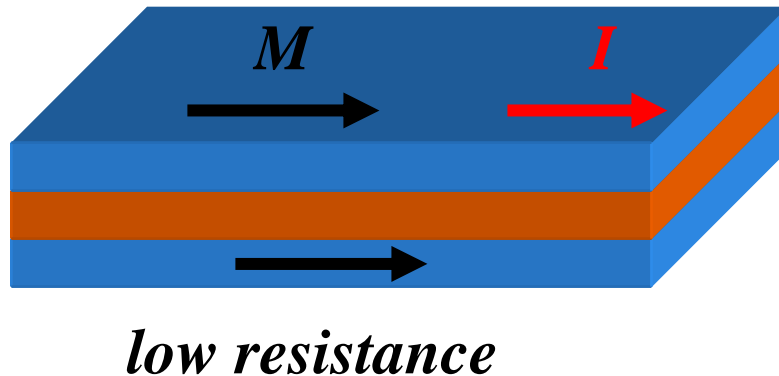
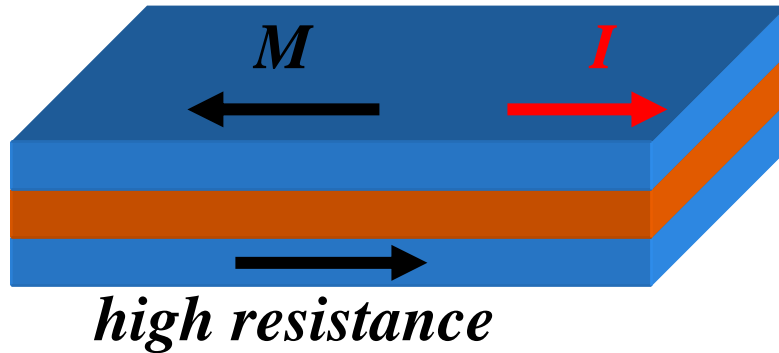


Bulk property of magnetic materials

AMR Sensor



Giant Magneto-resistance (GMR)

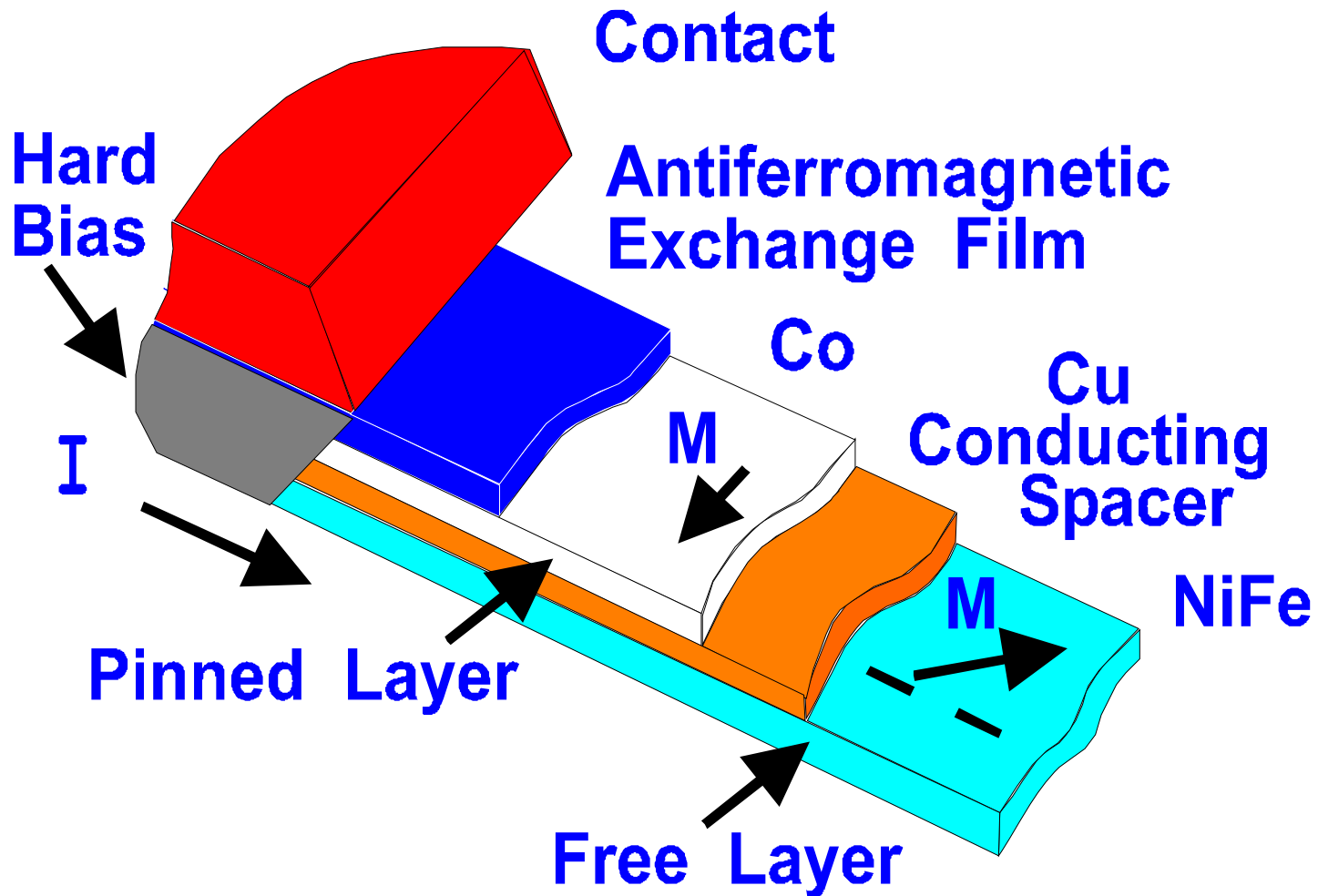


Interface property of magnetic materials

Baibich et al. Phys. Rev. Lett. **61** 2472 (1988)

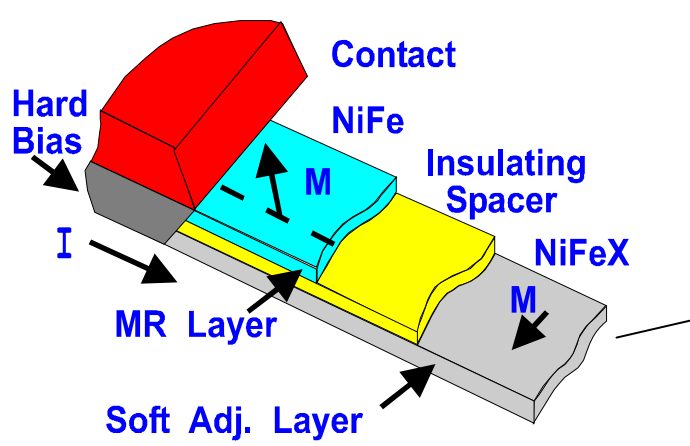
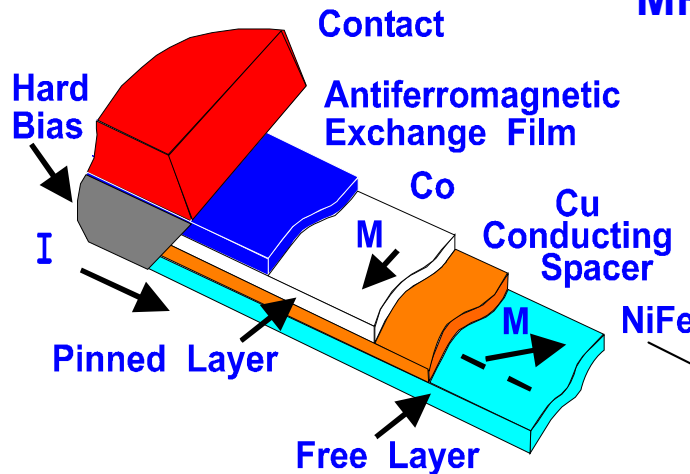
Binasch et al. Phys. Rev. B **39**, 4828 (1989); P. Grunberg, U.S. patent # 4,949,039

GMR sensor

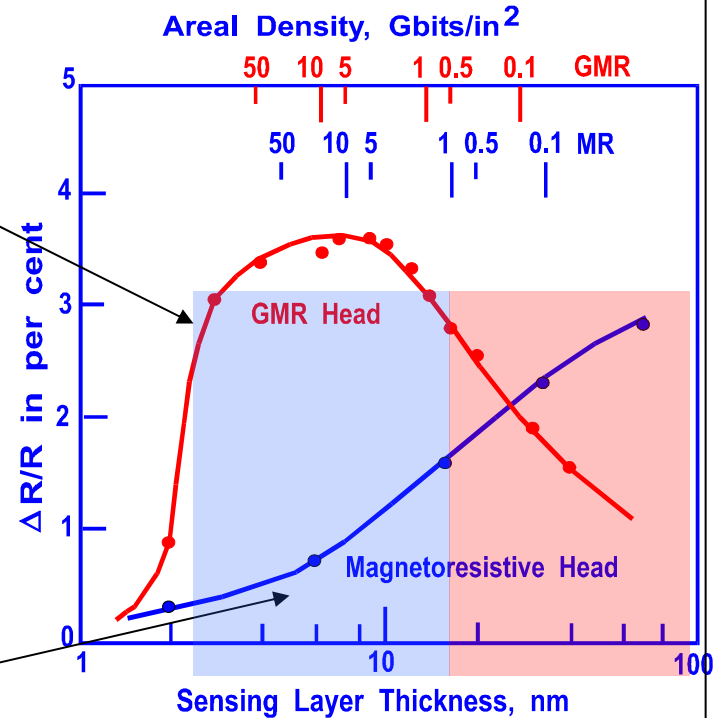


GMR sensors and scaling

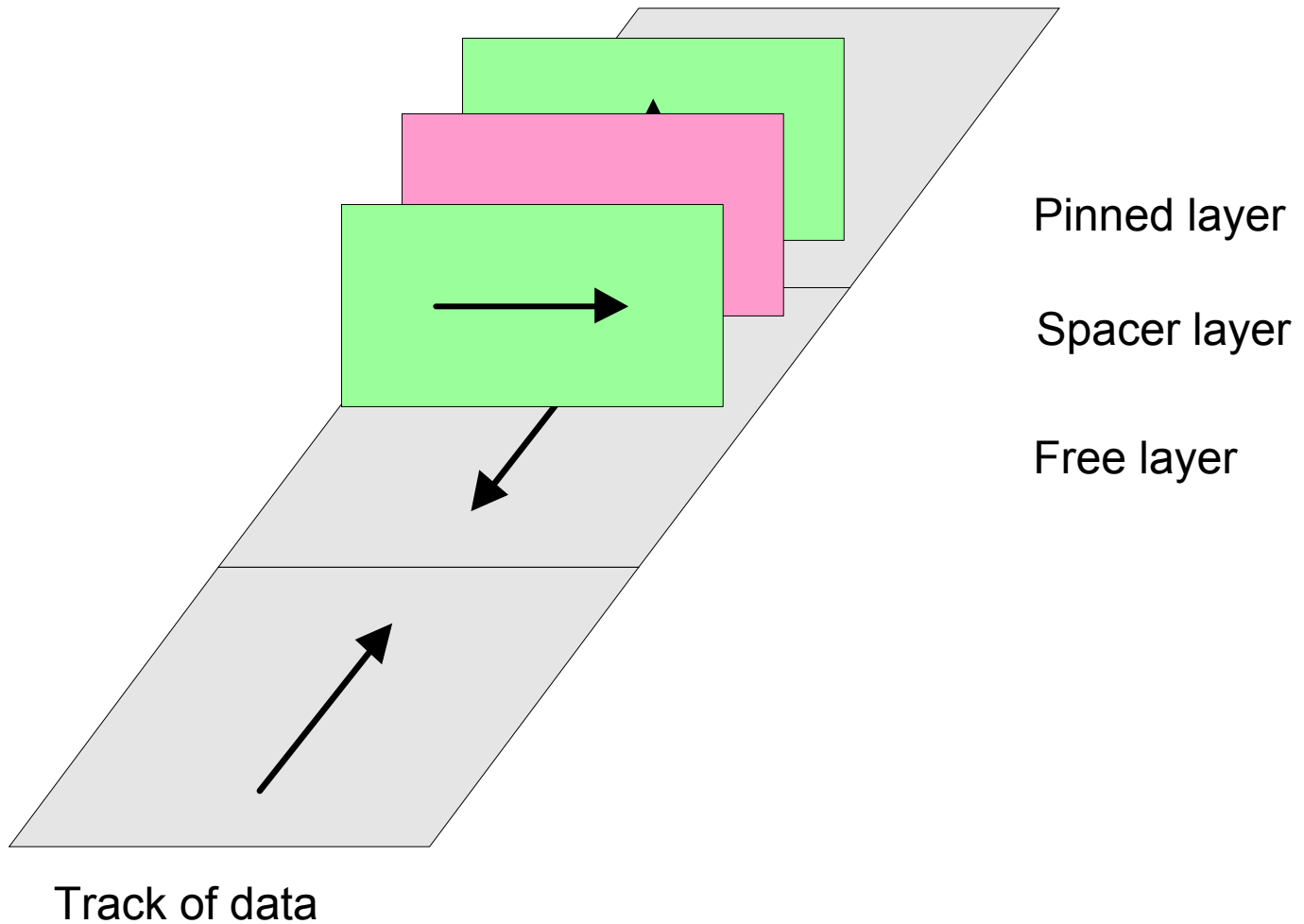
MR and GMR/Spin Valve Head Characteristics



Spin dependent scattering in a single alloy

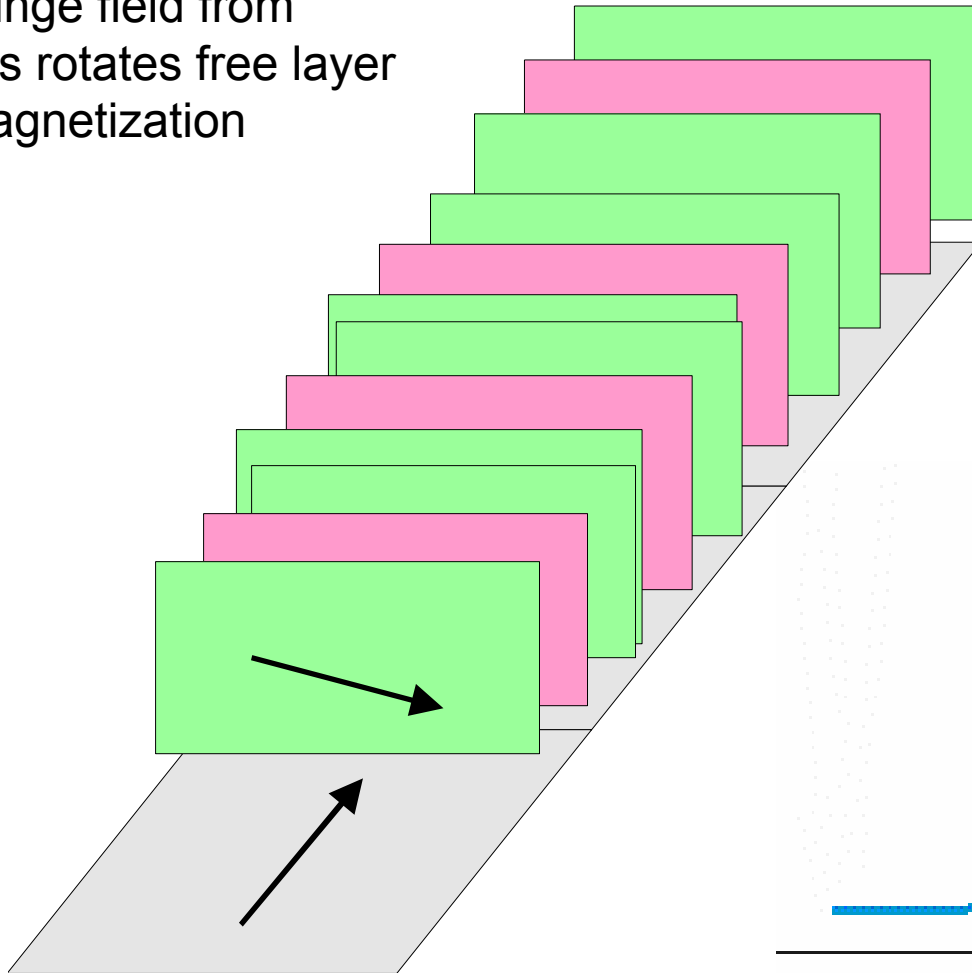


GMR sensors

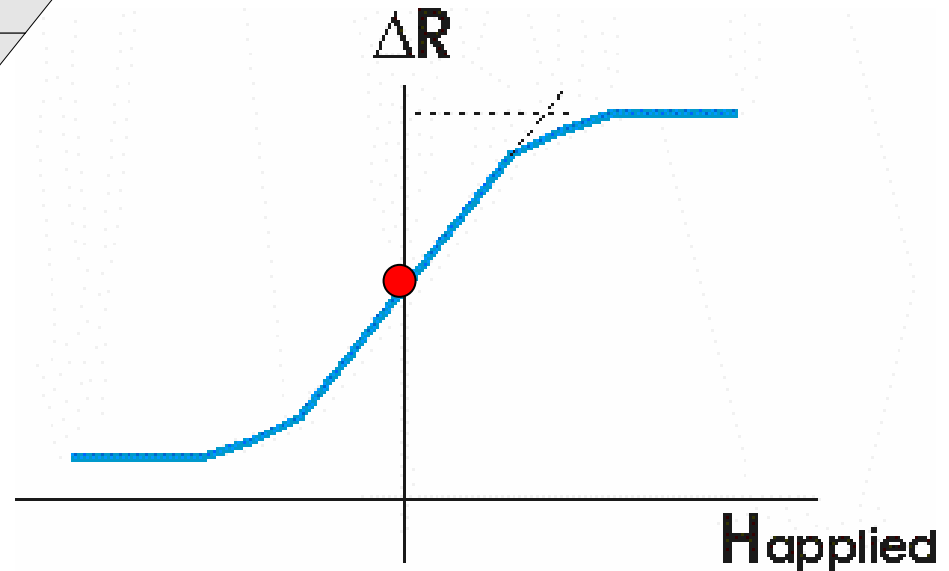


GMR sensors

Fringe field from bits rotates free layer magnetization

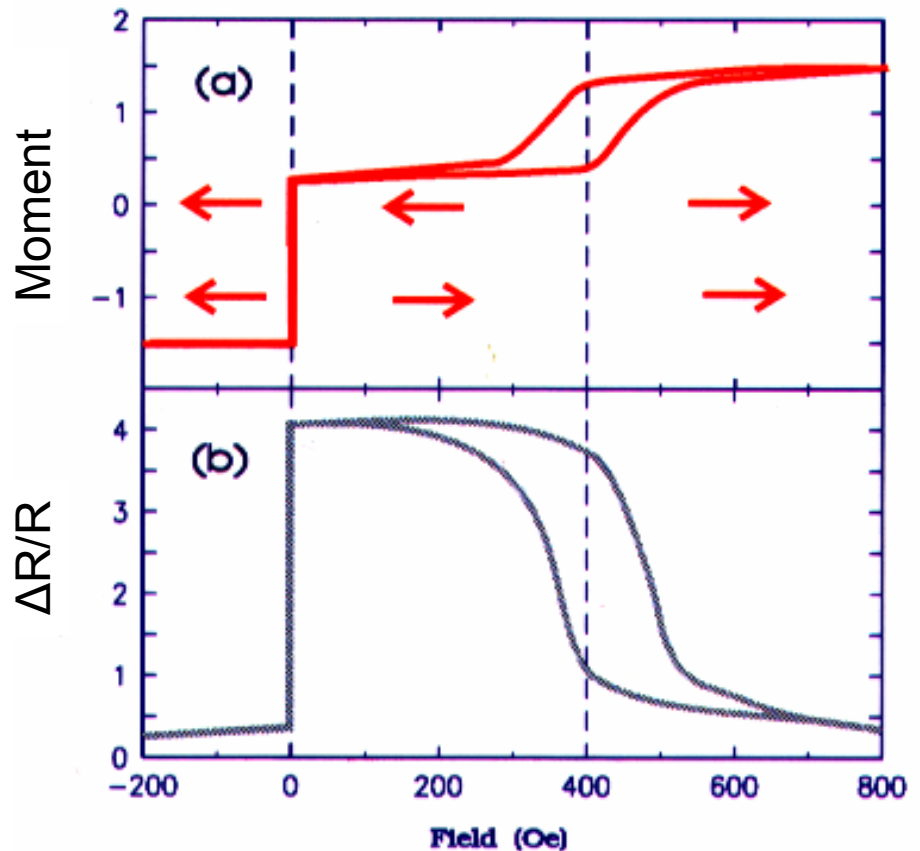
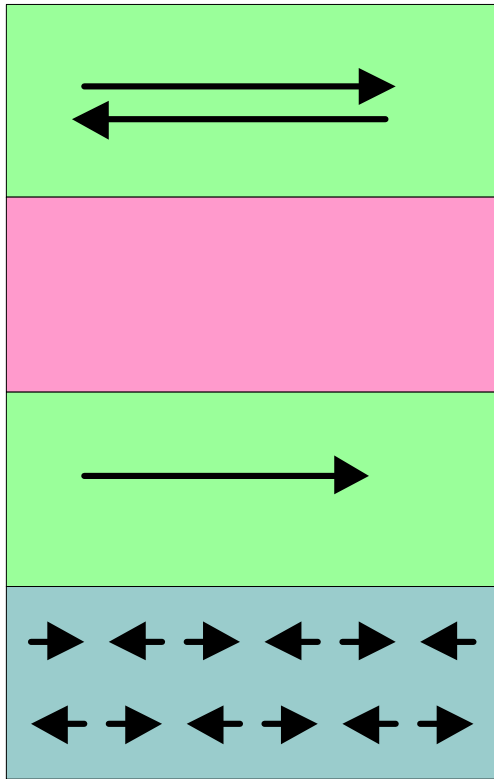


Track width

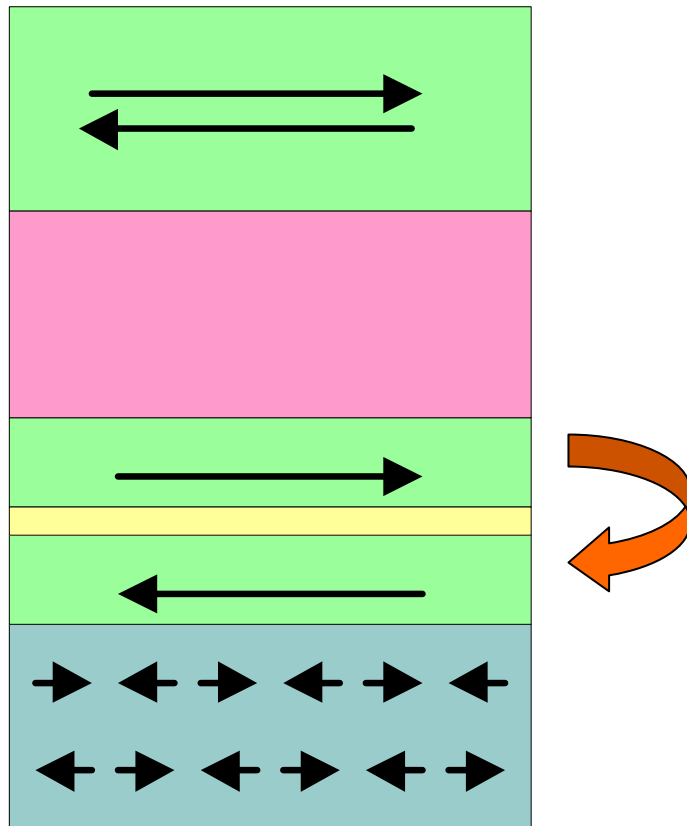


GMR sensors

- The reference ferromagnetic layer magnetization is pinned by an antiferromagnetic layer and does not rotate in small magnetic fields

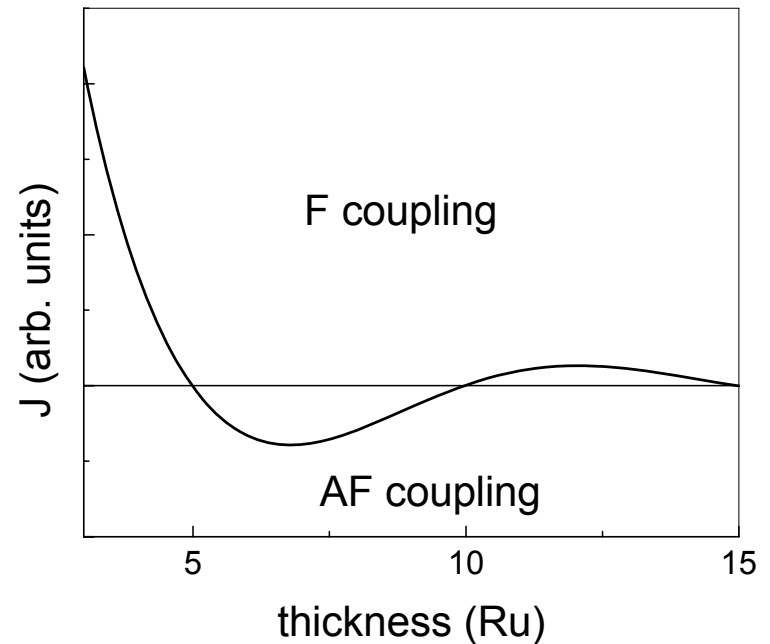


GMR sensors

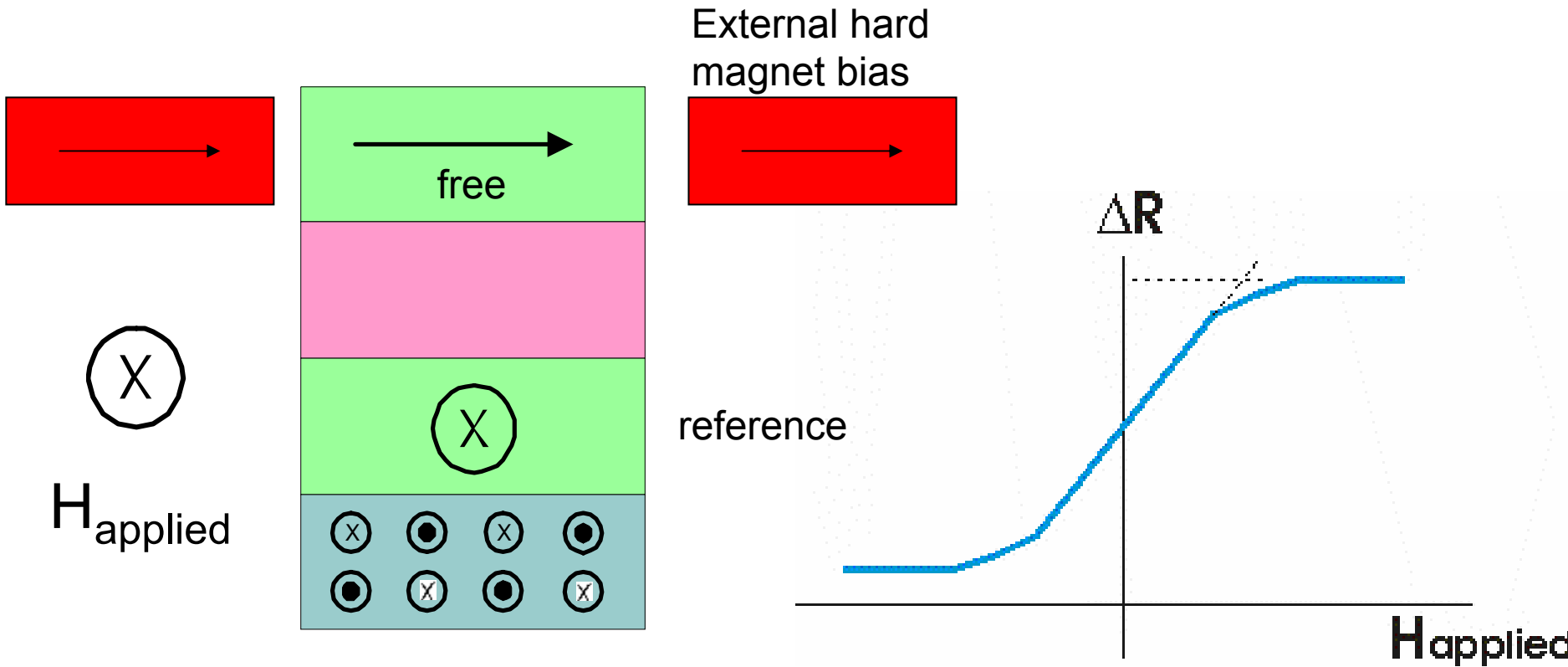


Pinned layer is AP pinned to obtain flux closure to minimize magneto-static coupling to free layer

Utilize AP coupling property of Ru, Ir...

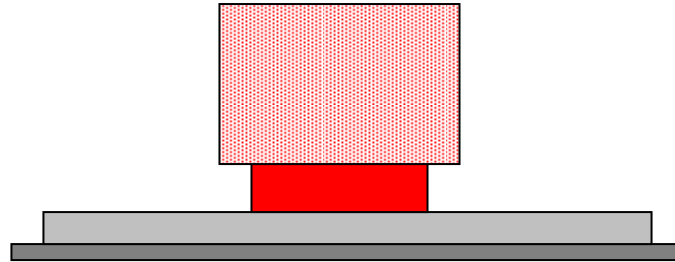


GMR sensors

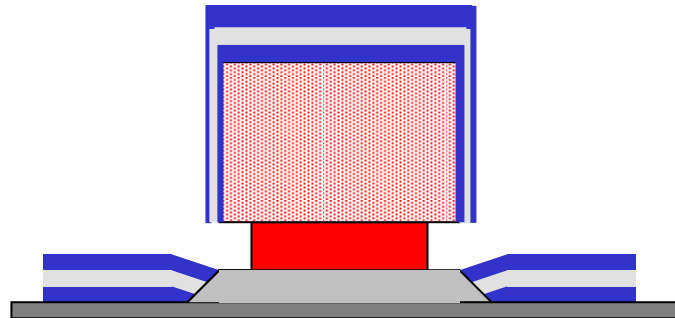


GMR sensors

- 1) Produce undercut resist structure (193nm photolithography)



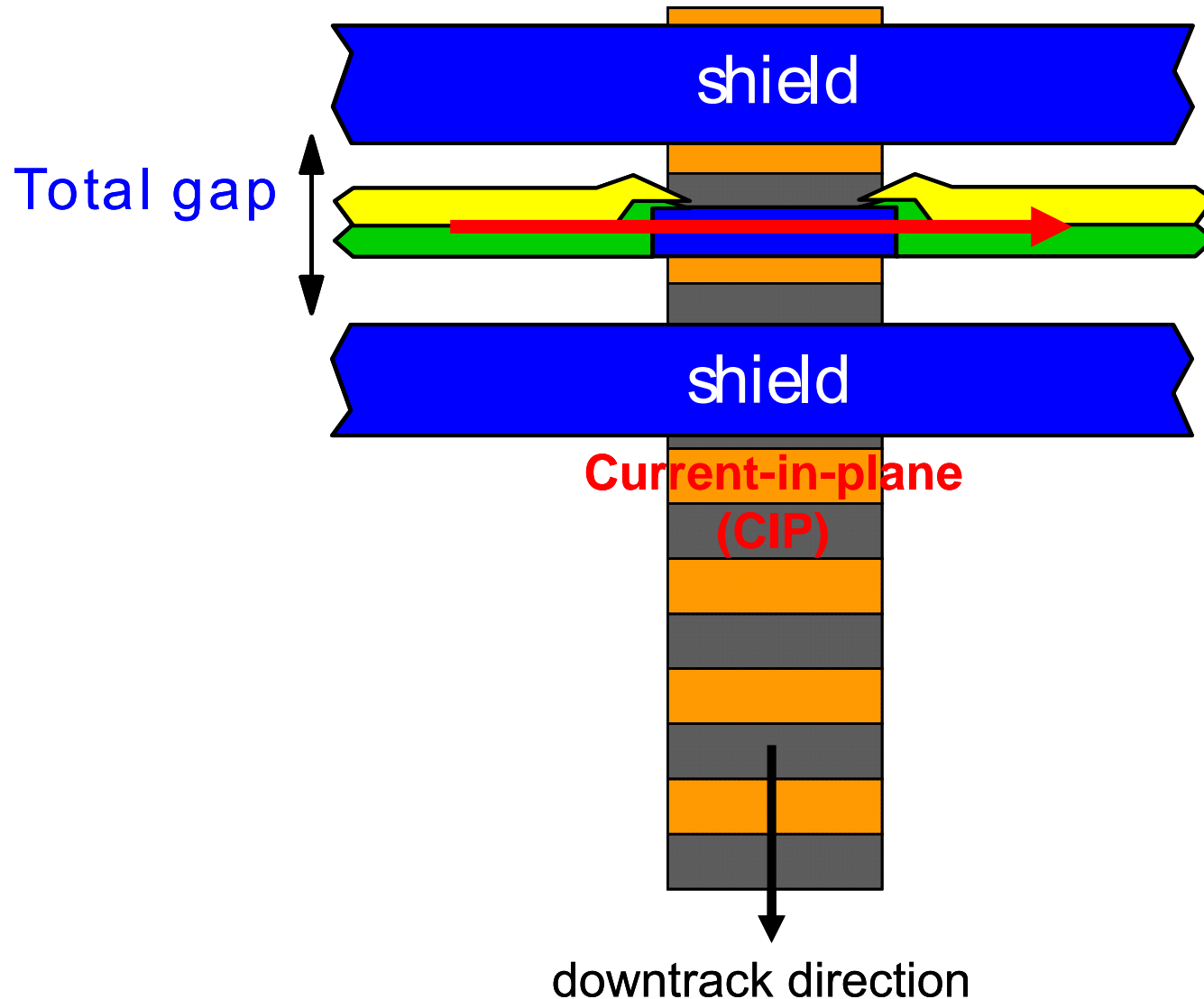
- 2) Ion Mill, then IBD HB/leads



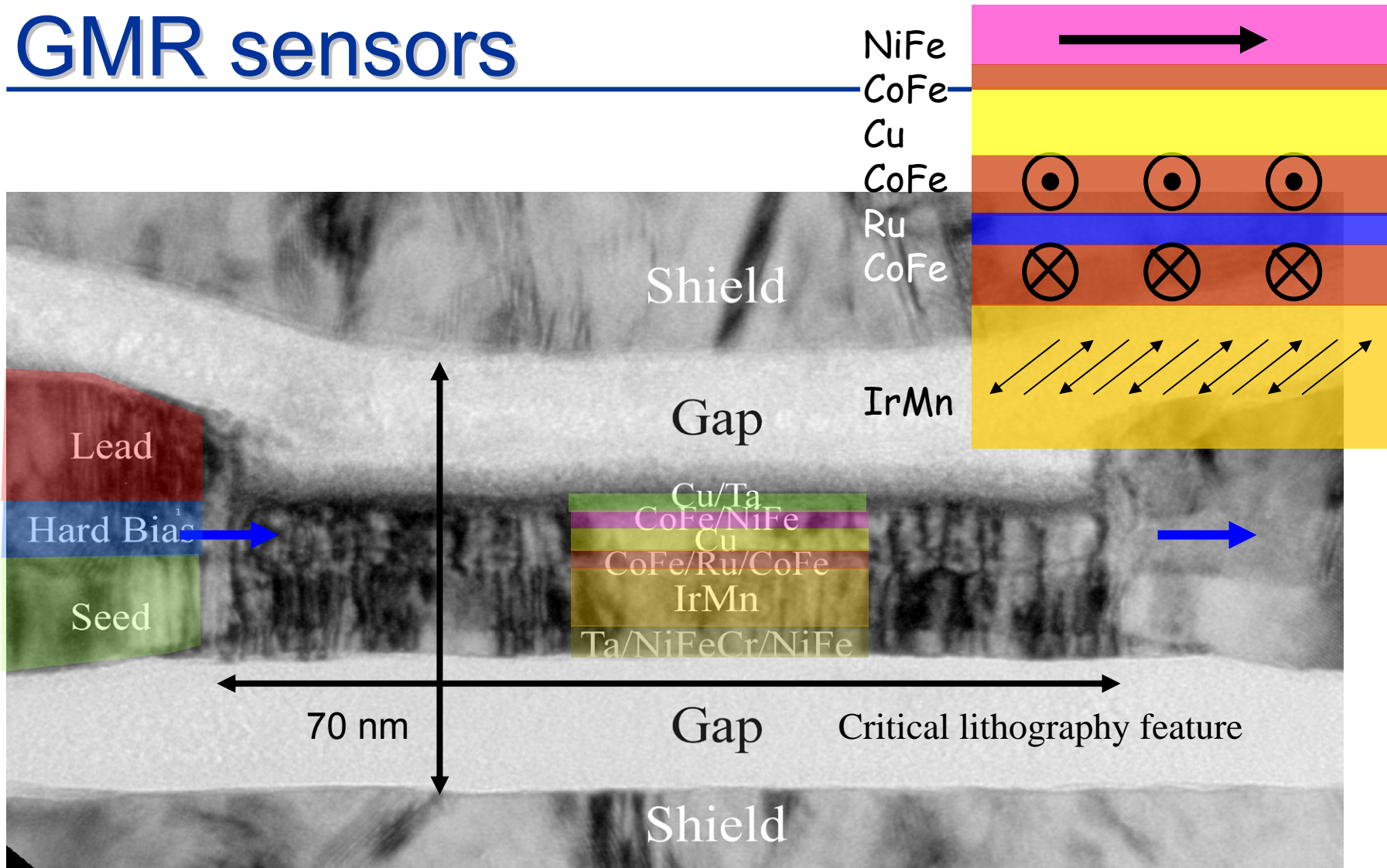
- 3) Lift-off Resist



GMR sensors and scaling



GMR sensors

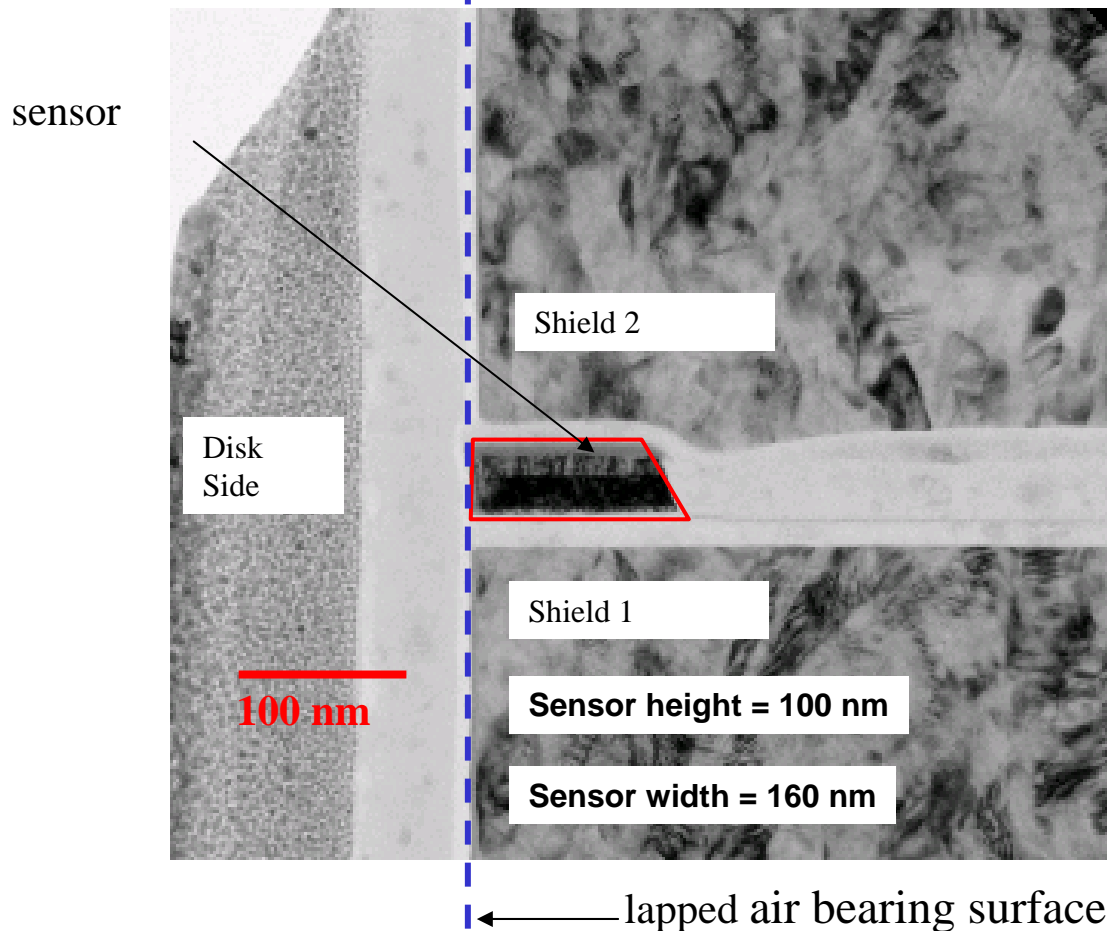


State-of-the-art magnetic hard disk drives

I. R. McFadyen, E. E. Fullerton and M. J. Carey, MRS Bulletin **31**, 379 (2006).

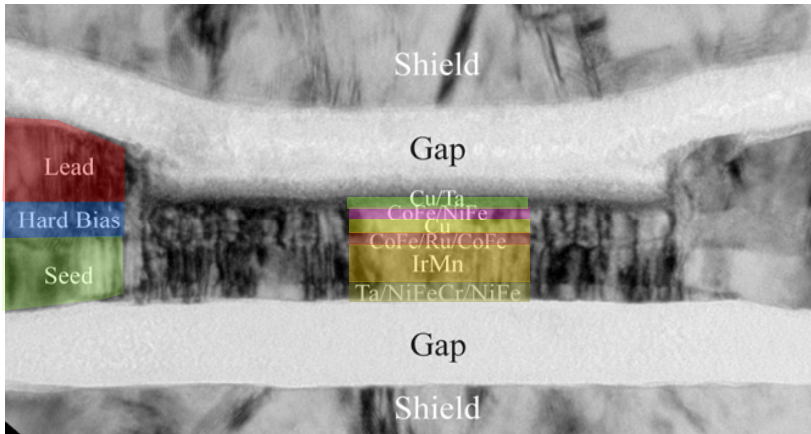
GMR sensors

- The height of the sensor is controlled by lapping (polishing) not by lithography.
- → The smallest feature in a thin film head is determined **mechanically**

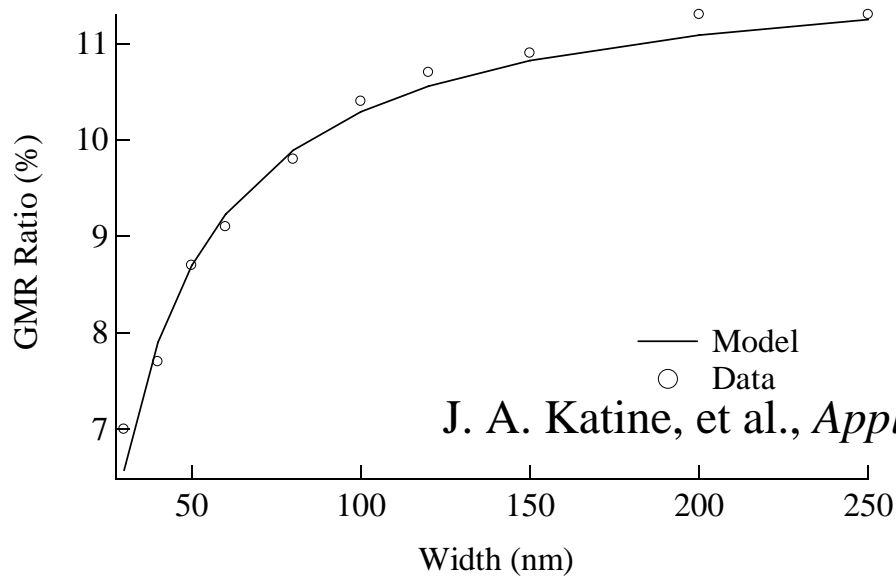


GMR read head

Works great, what's the problem

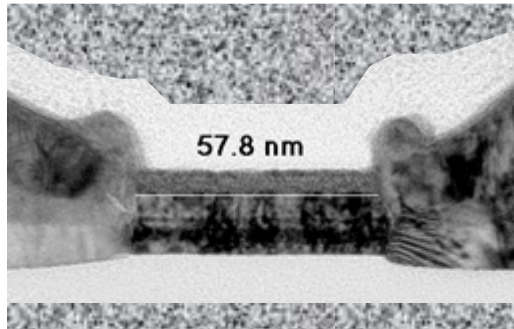


ΔR not increasing
R increasing
Shorting to the shields
Edge damage for small features

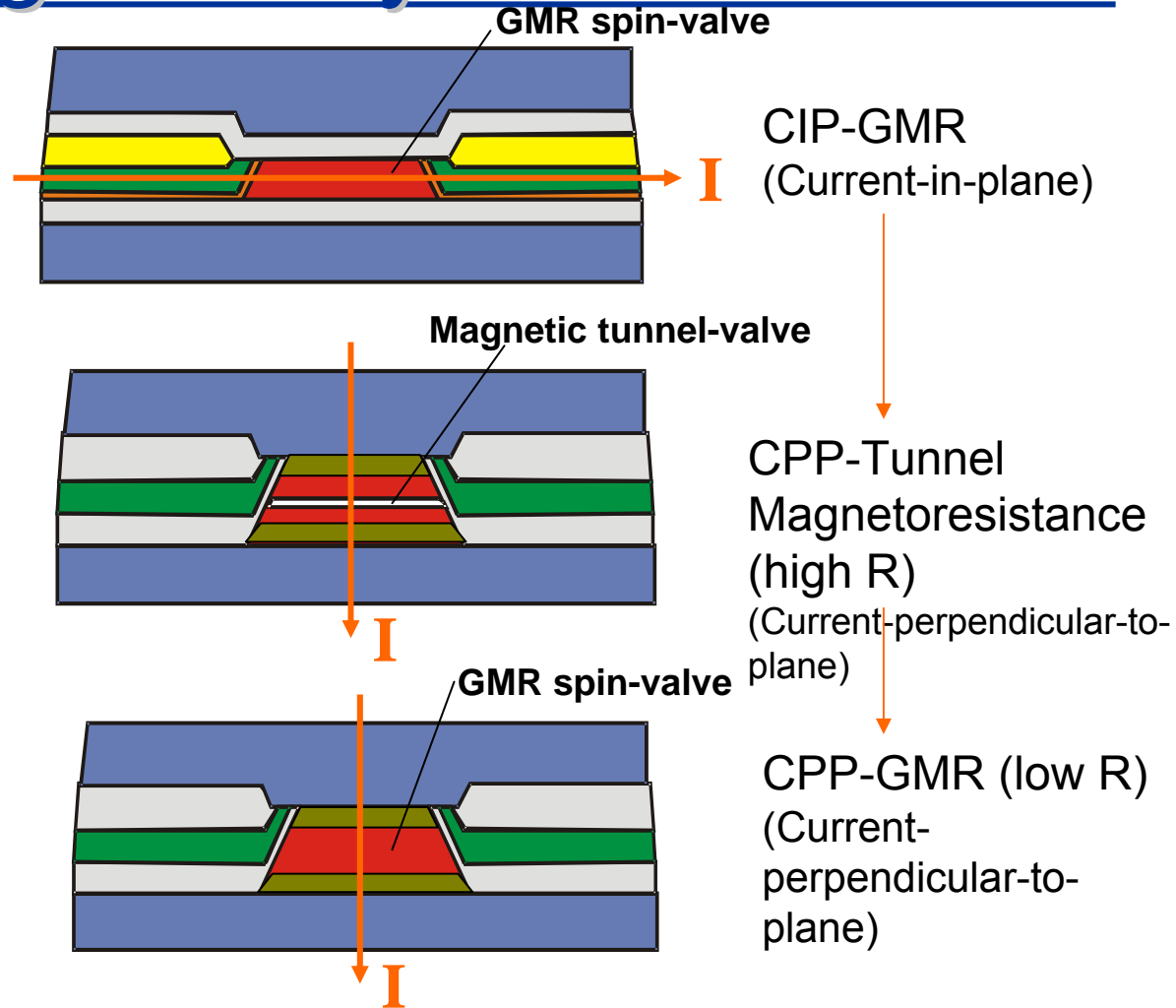
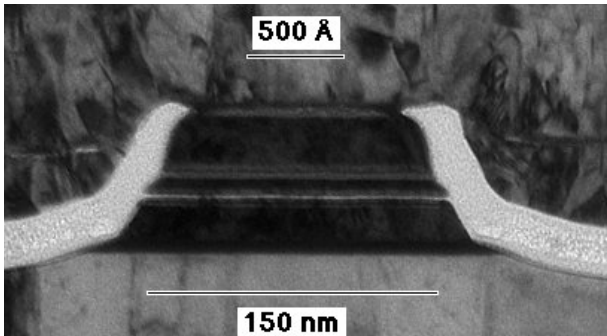


J. A. Katine, et al., *Appl. Phys. Lett.*, **83**, 401 (2003).

New sensor geometry



Tunnel-valve head

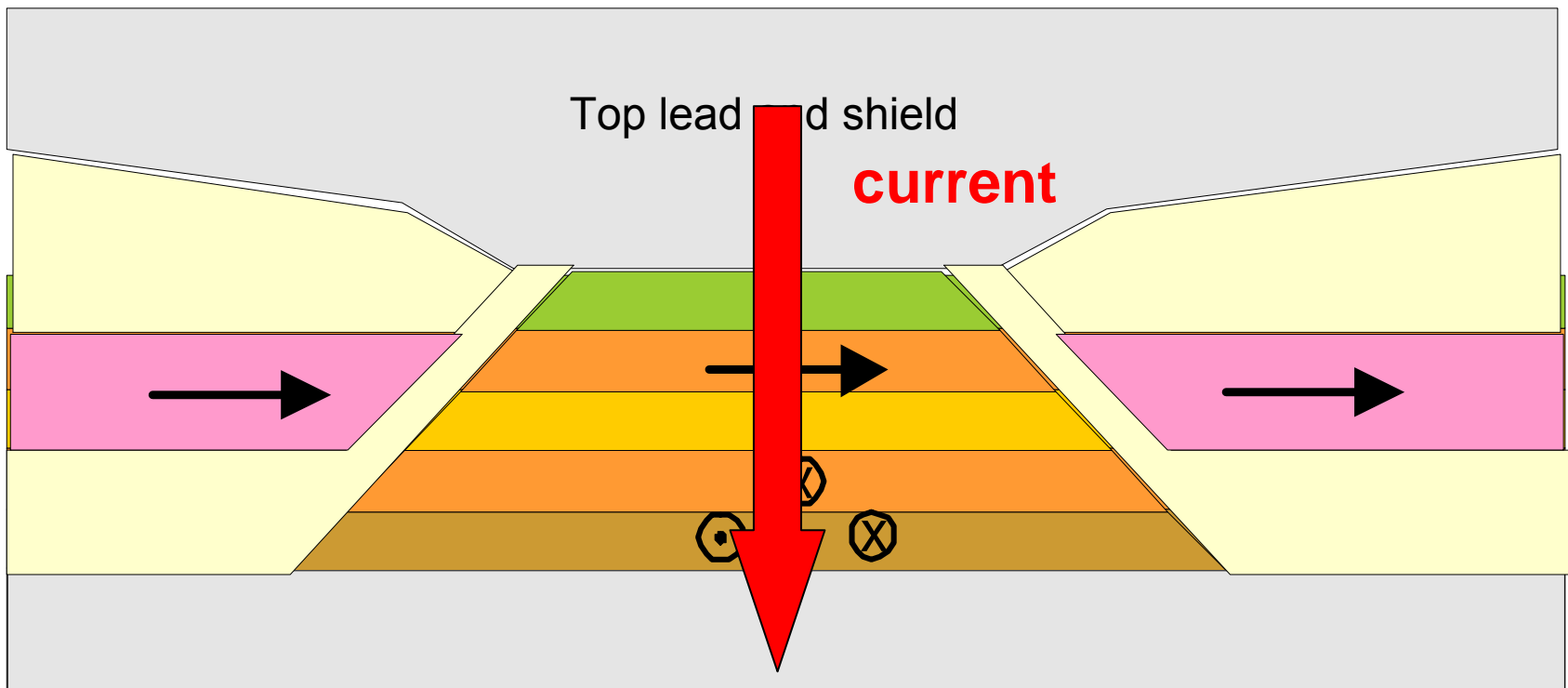


CPP sensor

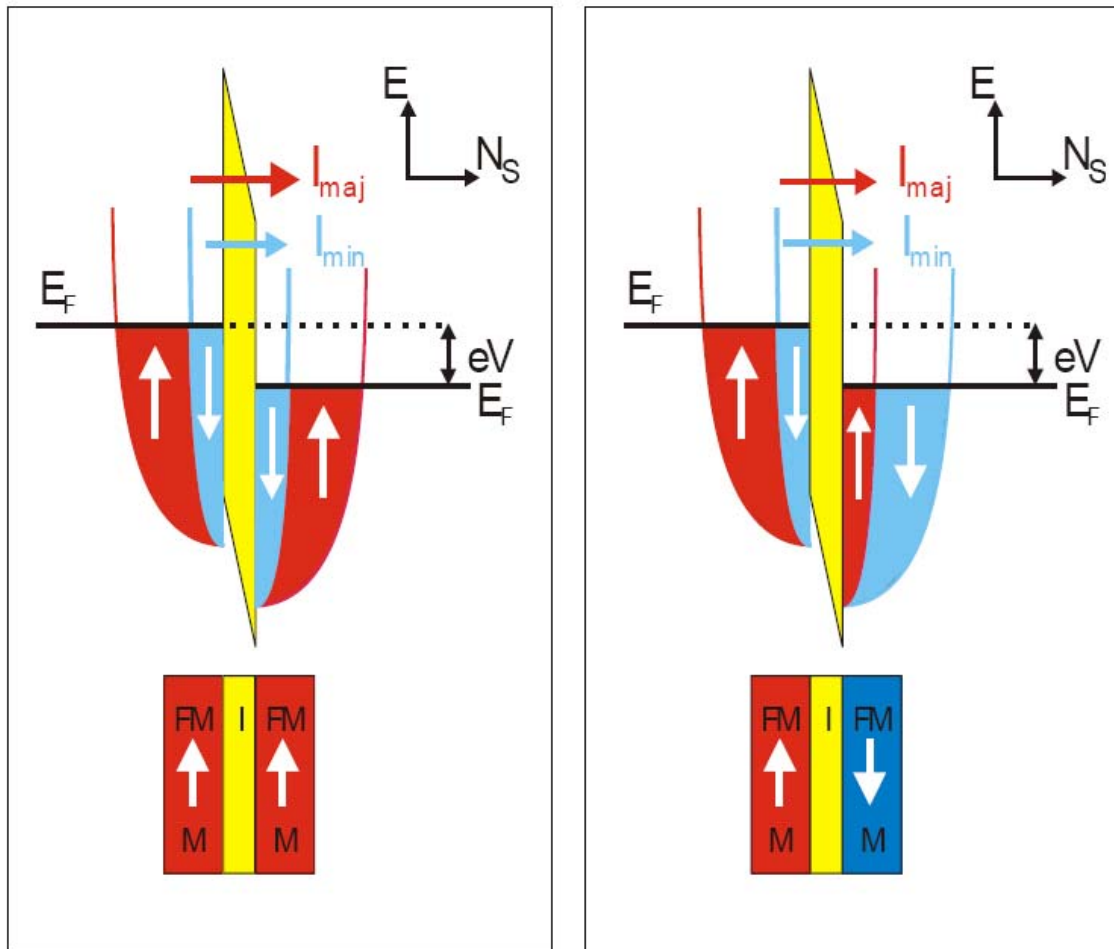
Sensor deposition

Photo/Ion mill

Insulator/hard bias deposition/Insulator deposition



TMR sensor



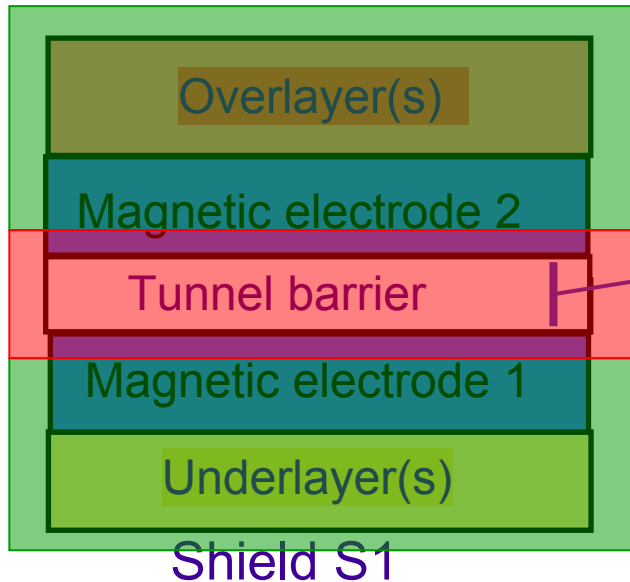
Juliere (1975)

$$MR = \frac{R_{AP} - R_P}{R_P} = \frac{2P_1P_2}{1 - P_1P_2}$$

$$\text{with } P = \frac{N_{\uparrow} - N_{\downarrow}}{N_{\uparrow} + N_{\downarrow}}$$



TMR sensor



1) Barrier + magnetic electrode interfaces determine maximum TMR
AlOx 70%TMR and MgO >500% TMR

2) Thickness of given barrier material
Determines $RA = \text{Resistance} \times \text{Area}$

3) TMR is independent of specific materials in sensor stack
→ Sensor design is highly flexible

Key goals:

- Smooth substrate+underlayers
- continuous ultrathin barrier growth
- Stable chemistry @ barrier interfaces
- No shunting of barrier during lithography

TMR sensor

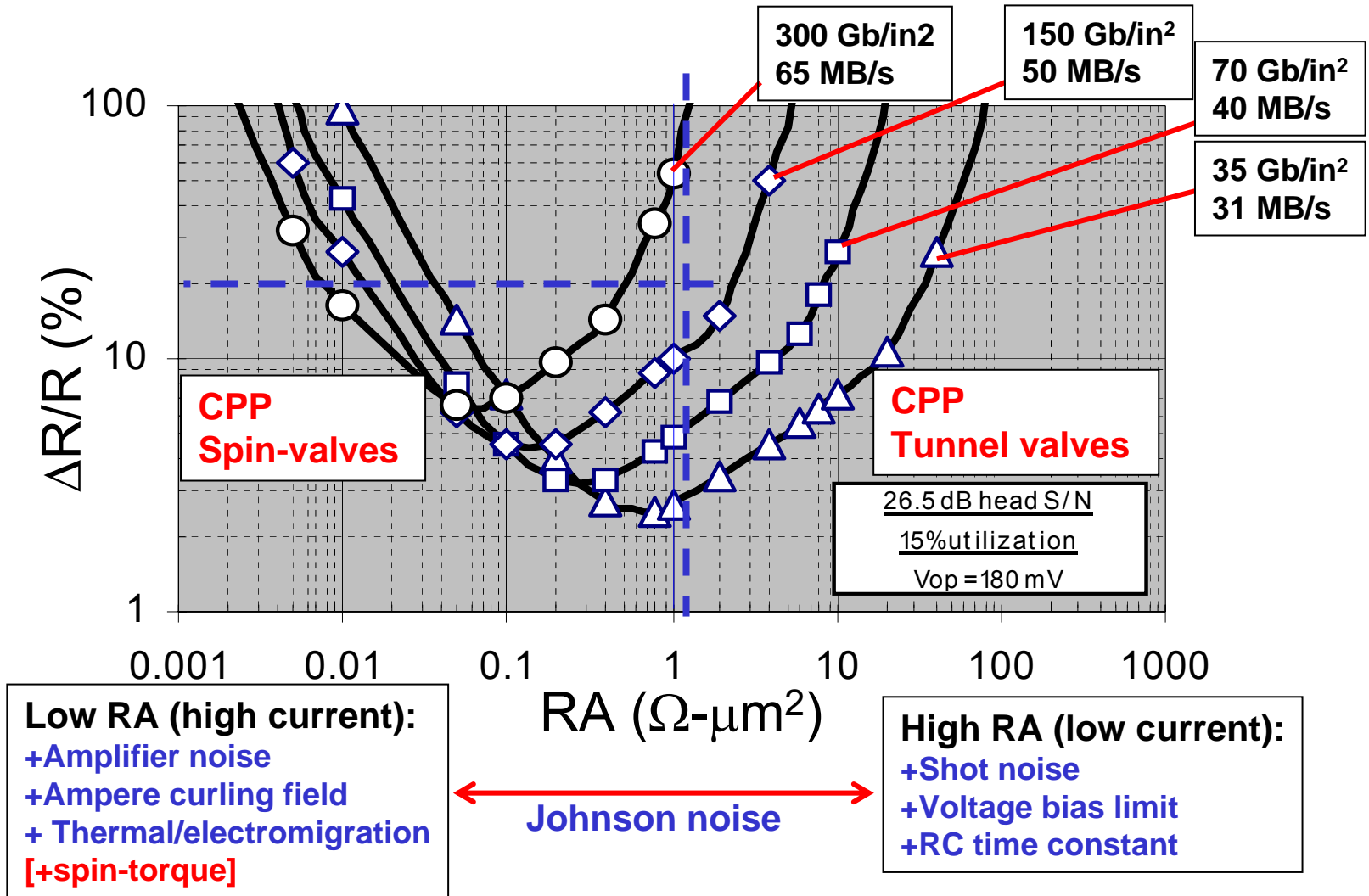
The resistance of the device depends on RA product

R (per unit area) depends exponentially on the barrier thickness

A is set by size of the bits (decreases with time).

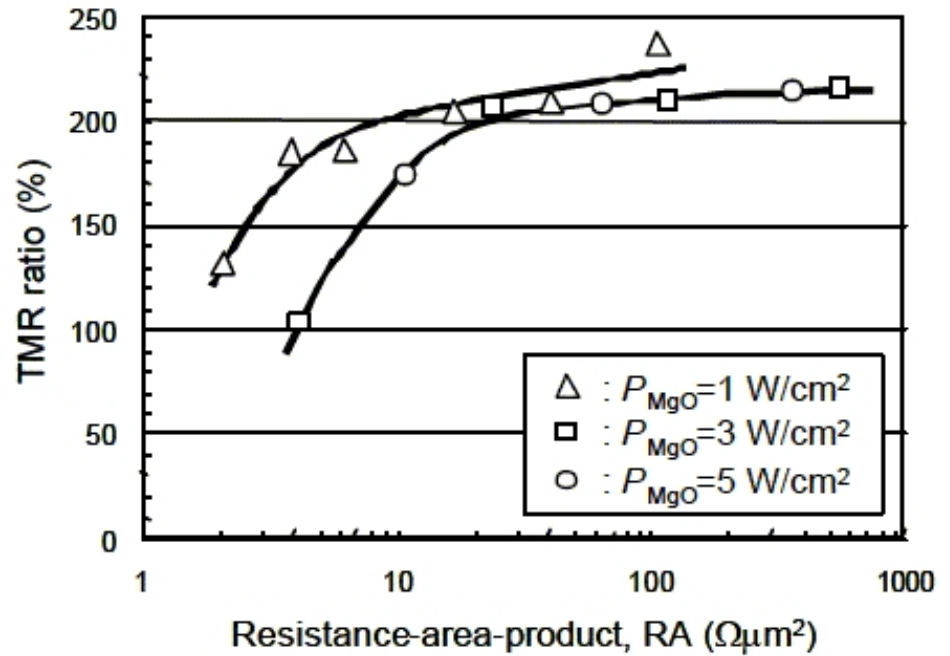
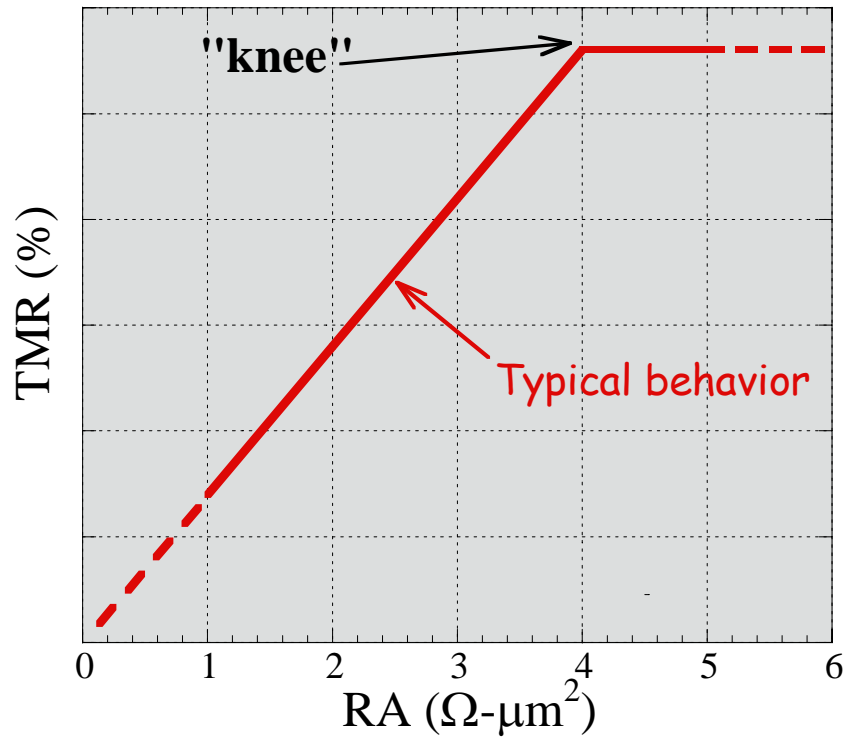
To keep the resistance of the device constant you need to thin the barrier over time (or find lower R barrier materials).

TMR sensor



TMR sensor

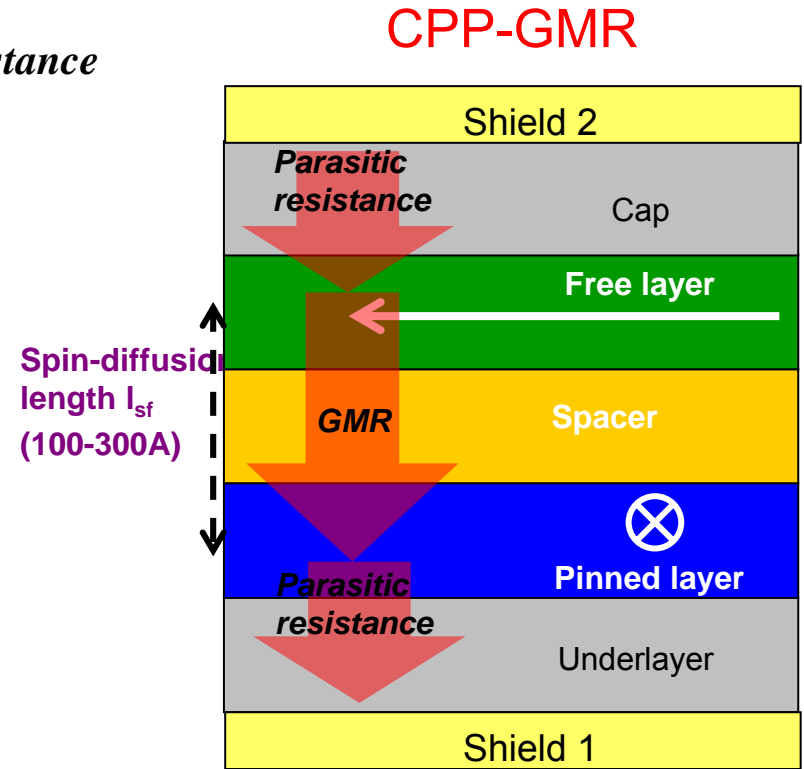
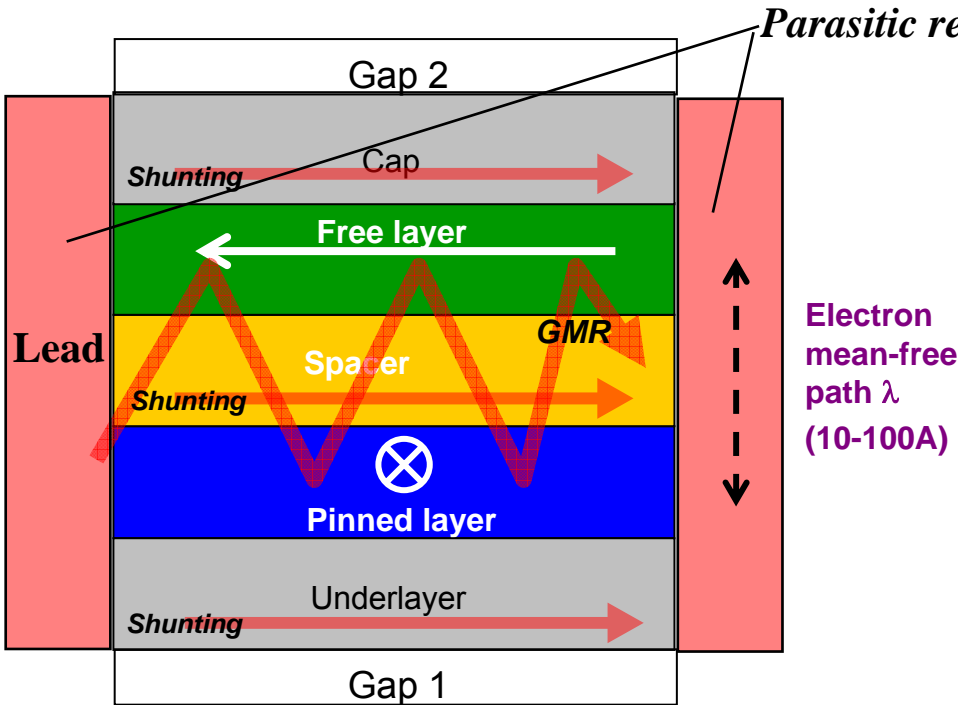
CoFeB/MgO/CoFeB



Y. Nagamine et al. (Anelva corp.)
Intermag '06

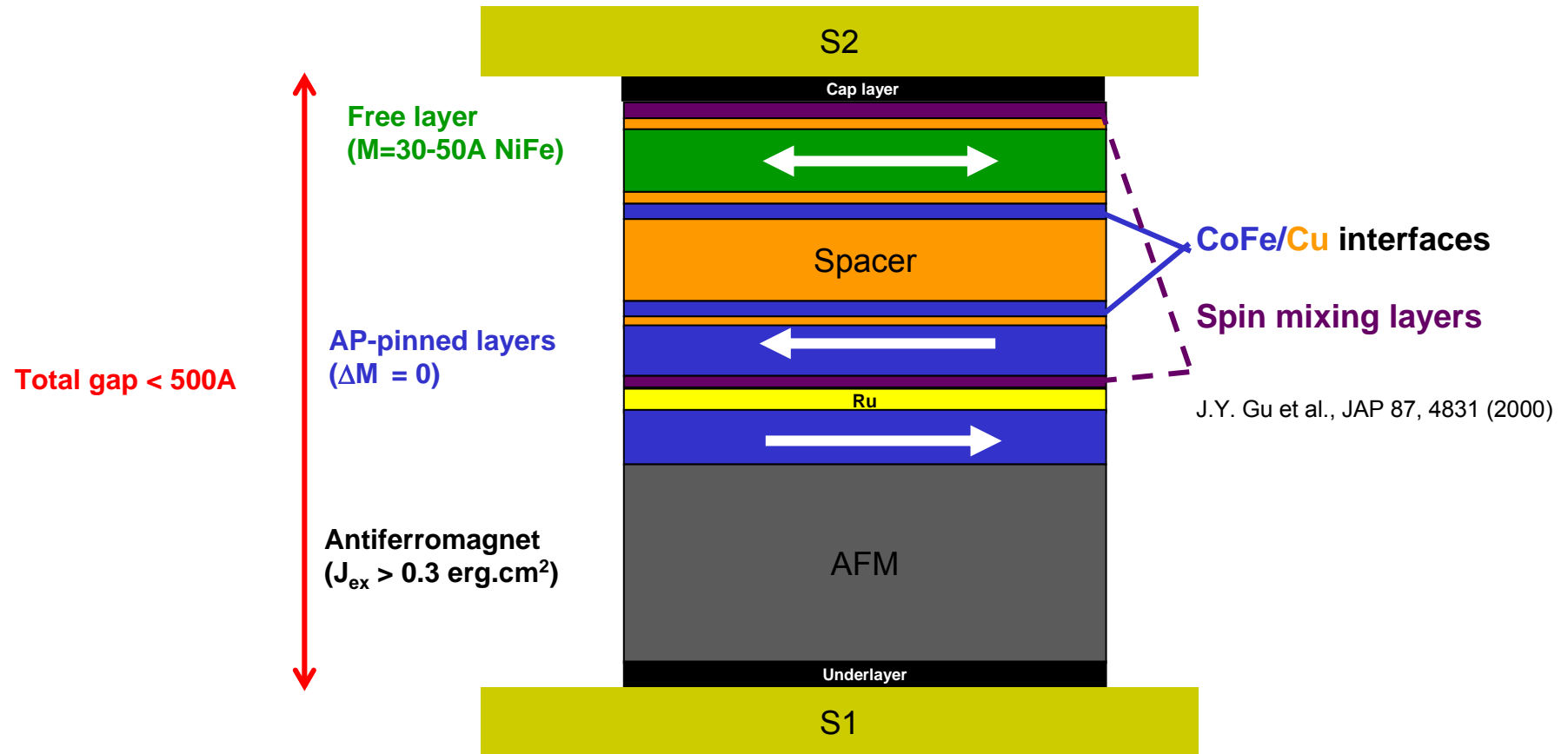
CPP GMR Sensor

In absence of low RA tunnel barrier move to metal devices.



CIP-GMR Shunting effect limits maximum signal

CPP GMR Sensor



CPP GMR Sensor

Compared to TMR, CPP GMR has lower R , ΔR & $\Delta R/R$

So how to get a signal?

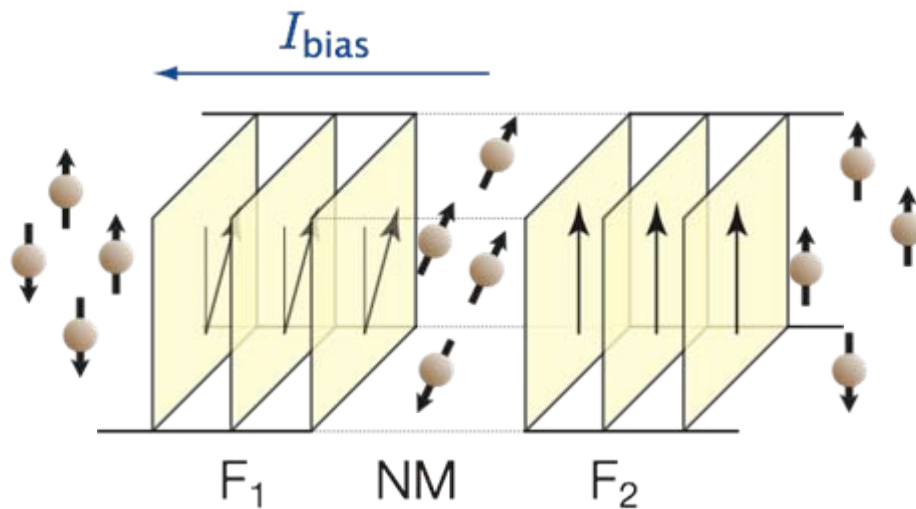
Current: $> 10^8 \text{ A/cm}^2$

Heating

Electromigration

Spin - transfer torques

Spin transport



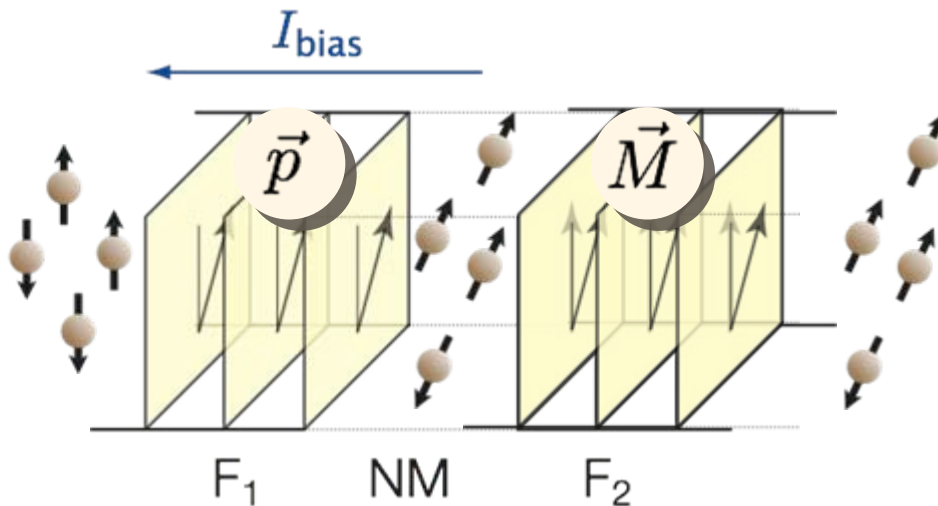
$$R \sim R_0 + \Delta R (1 - \cos(\theta))$$

GMR metallic

TMR insulator

Spin transfer effect

J. Slonczewski, J. Magn. Magn. Mater. 159, L1 (1996)
L. Berger, Phys. Rev. B 54, 9353 (1996)



- Current polarized by F1
- Transfer of spin angular momentum to M
- $J \sim 10^7 \text{ A/cm}^2$

$$\vec{T}_I = \frac{\omega_t}{M_0} \vec{M} \times (\vec{p} \times \vec{M})$$

Magnetization dynamics

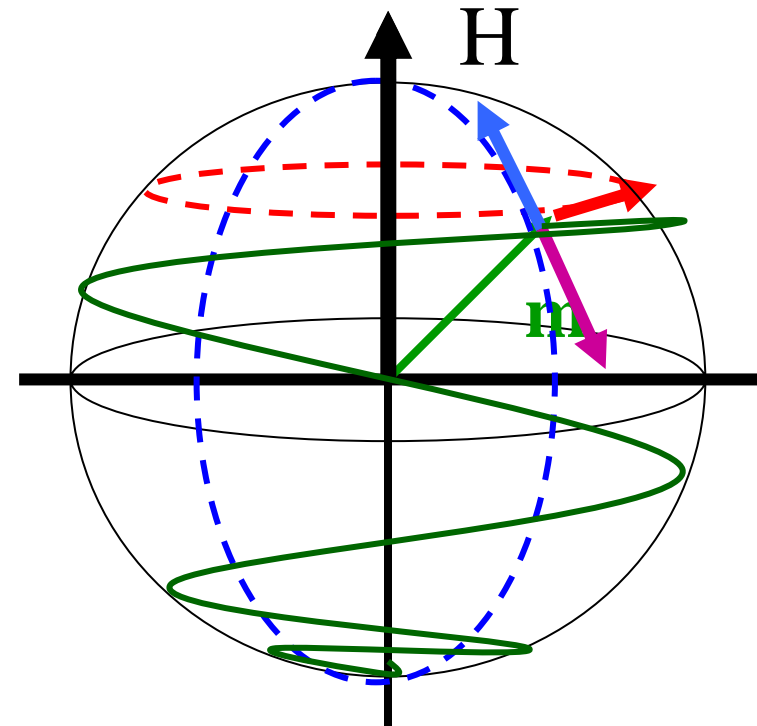
$$\frac{d\mathbf{m}}{dt} = \gamma_0 \mathbf{H} \times \mathbf{m} + \alpha \left(\mathbf{m} \times \frac{d\mathbf{m}}{dt} \right)$$

Field torque
(precession)

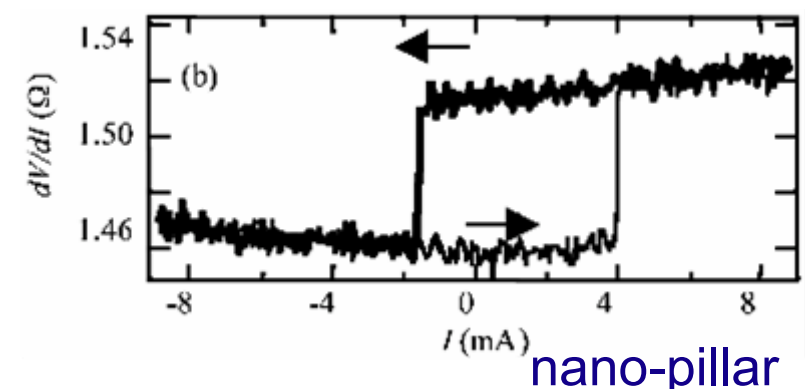
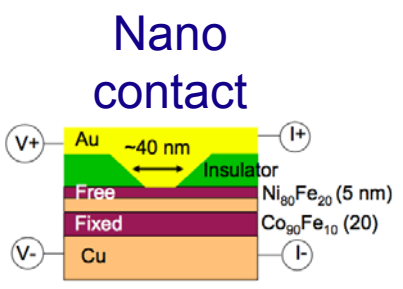
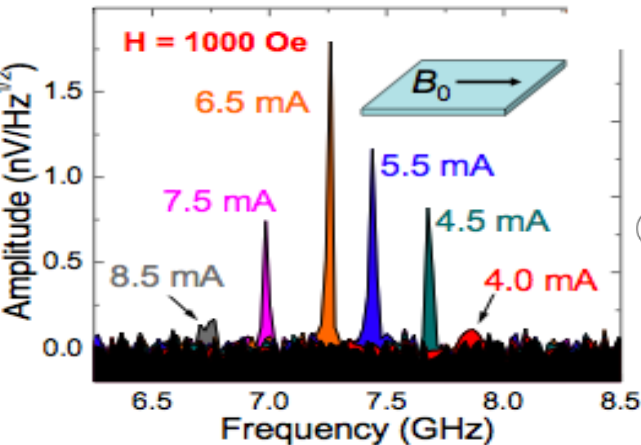
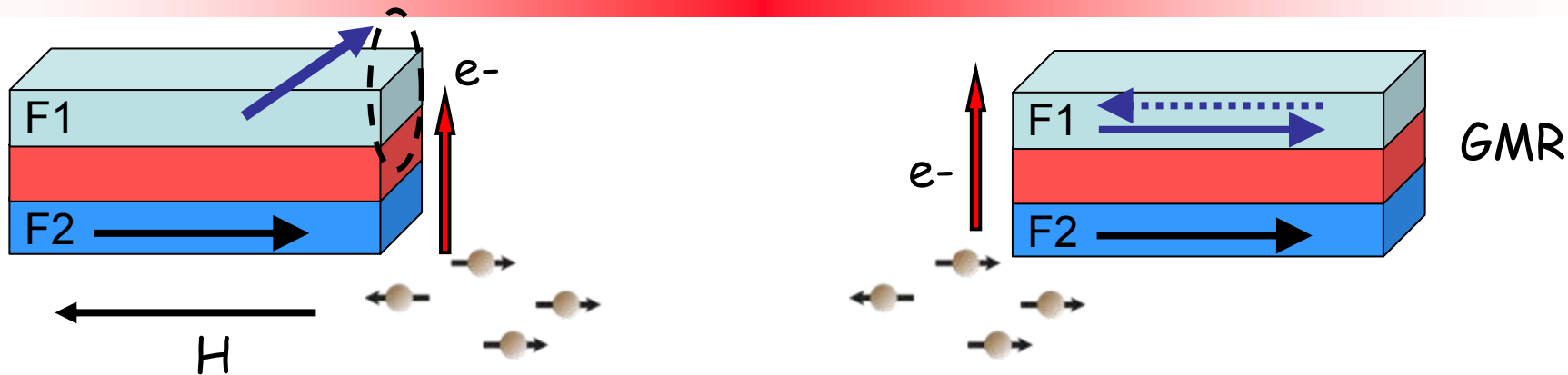
Damping torque
(dissipation)

$$-\frac{IP_i g \mu_B}{eM_s t} (\mathbf{m} \times (\mathbf{m} \times \mathbf{p}))$$

Spin torque
(negative friction)



Magnetization dynamics

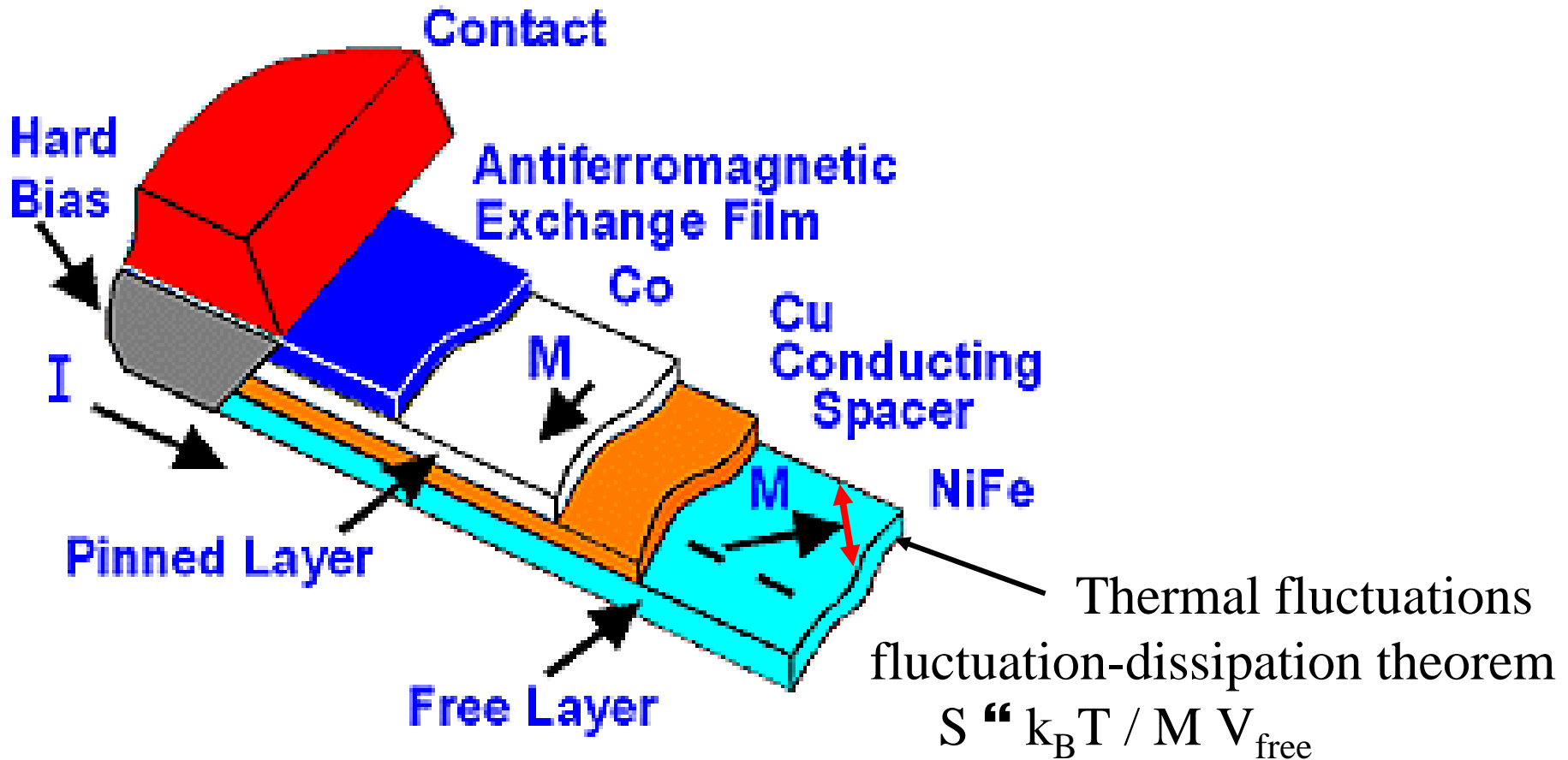


M. Tsoi et al., Phys. Rev. Lett. **80**, 4281-4284 (1998)
 W. H. Rippard et al., Phys. Rev. Lett. **92**, 027201 (2004)

J.A. Katine et al., Phys. Rev. Lett. **84**, 3149 (2000)

$$I_C^{P-AP} \approx \frac{A\alpha M_S V}{g(0)p} (H + H_{dip} + H_{K//} + 2\pi M_S)$$

GMR sensor



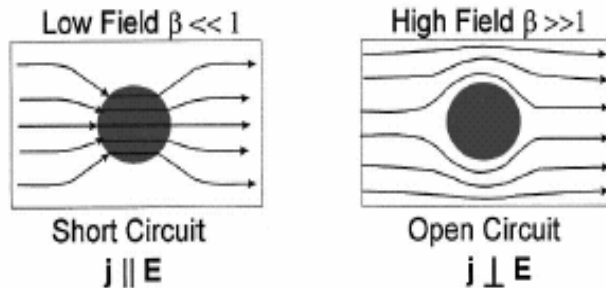
Smith and Arnett, APL **78**, 1448 (2001).

Sensors

Sensors need a lot of properties
not just $\Delta R/R$

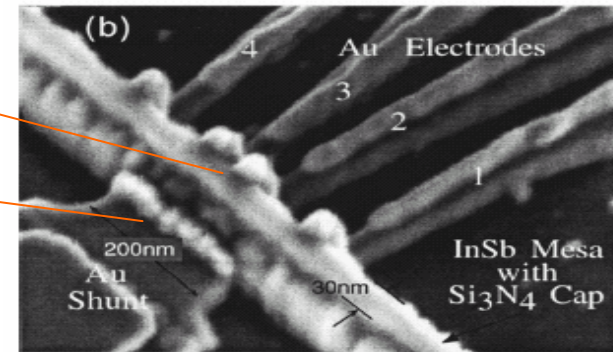
Opportunities for new materials
and new phenomena

Non-magnetic magnetic sensors



High-mobility SC

Metal shunt

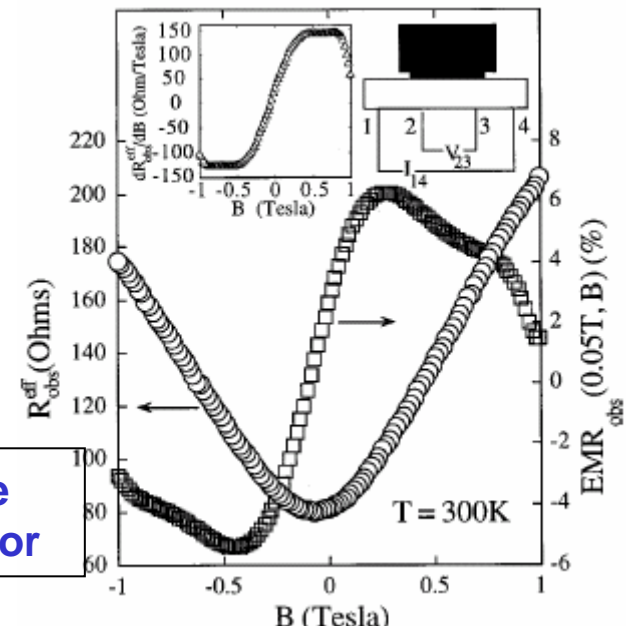


Solin, APL 80, 4012 (2001)

Metal dot embedded in high mobility low carrier density semiconductor (i.e. InSb).

At low field E is \perp to metal/SC boundary and j follows $E \rightarrow$ low R .

At high fields because of the Lorentz force the angle between j and E can approach 90 degrees with little current flowing through metal \rightarrow high R .



- Attractive because immune from magnoise, spin-torque
- However geometry is challenging for a slider-type sensor